

Cold Neutron Reflective Optics for $n\bar{n}$

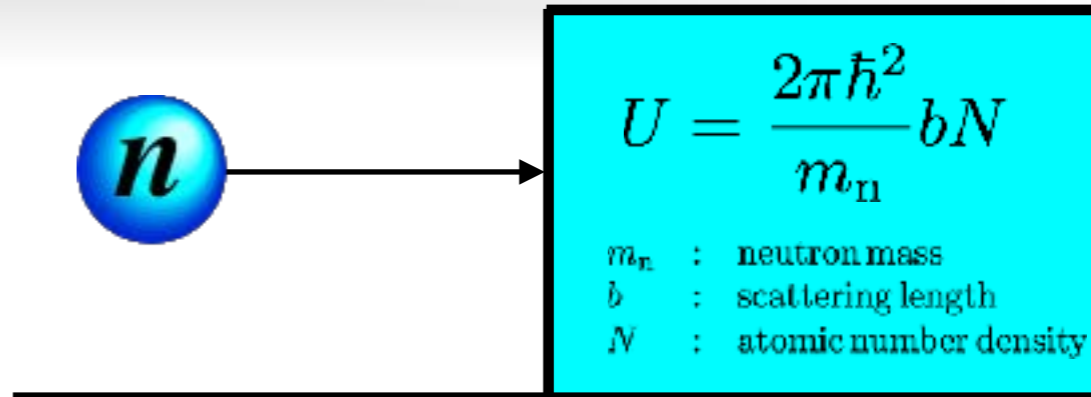
Kosuke NAGAMOTO, Takahiro MORISHIMA, Go ICHIKAWA,
Masaaki KITAGUCHI and **Hirohiko M. SHIMIZU**

Department of Physics, Nagoya University

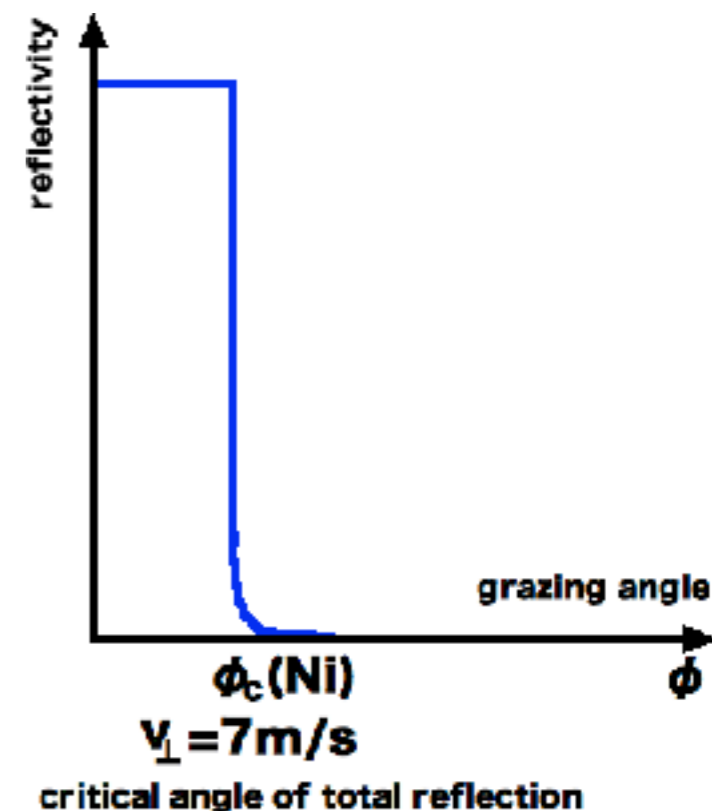
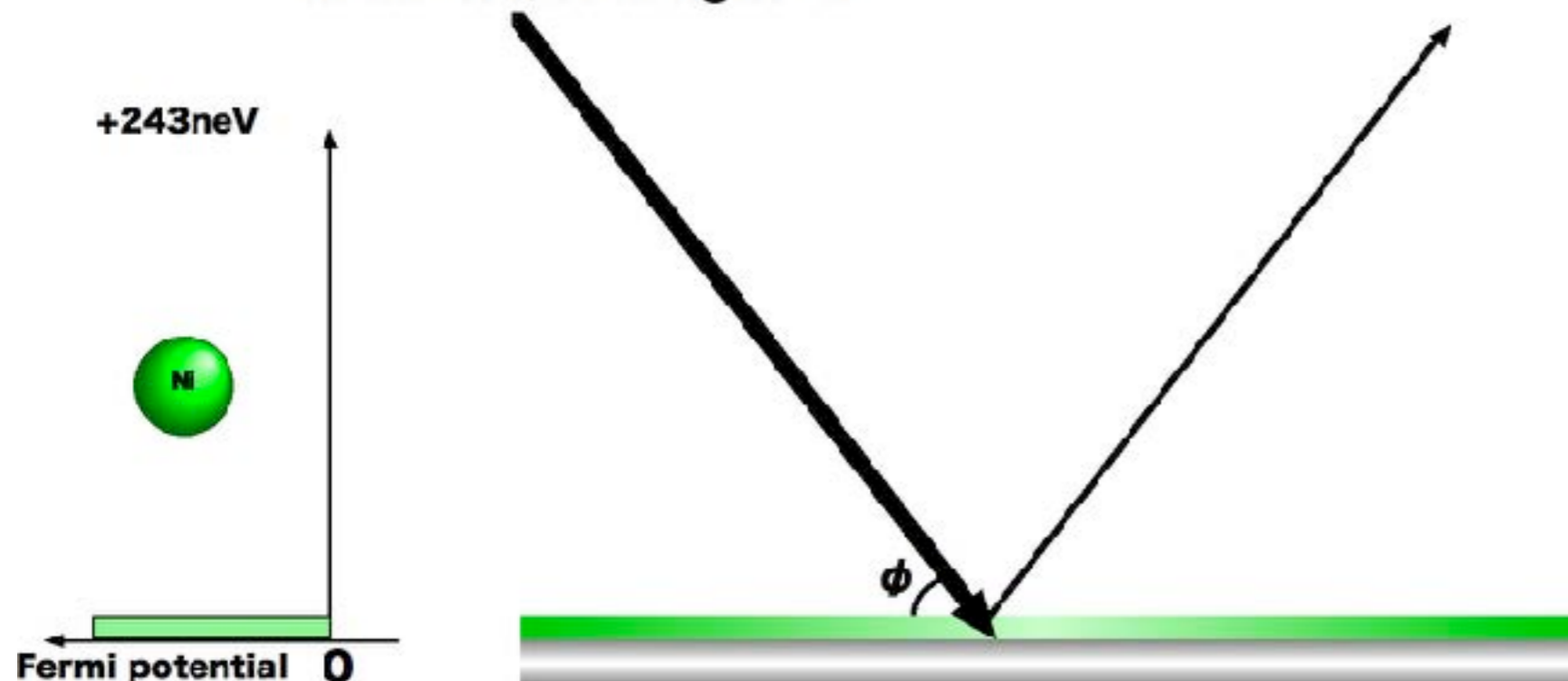
neutron reflection

Neutron Reflection

Fermi pseudopotential



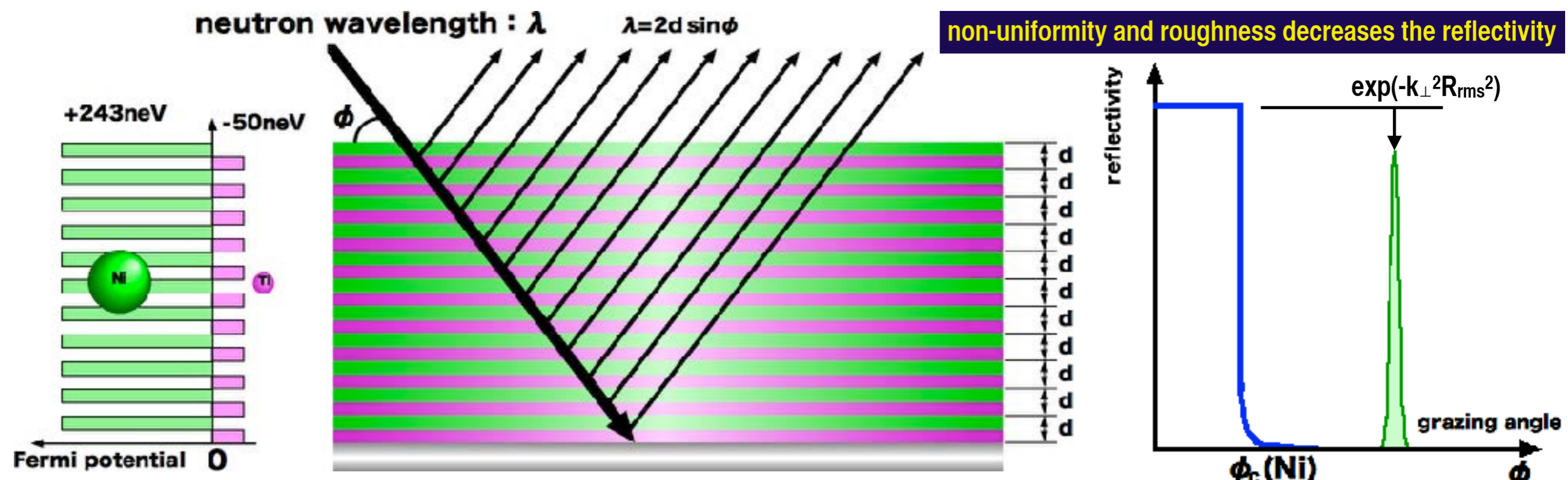
neutron wavelength : λ



$$\frac{\phi_c(\text{Ni})}{\lambda_n} = 1.7 [\text{mrad } \text{\AA}^{-1}]$$

$$v_{\perp}(\text{Ni}) = 7 \text{ m/s}$$

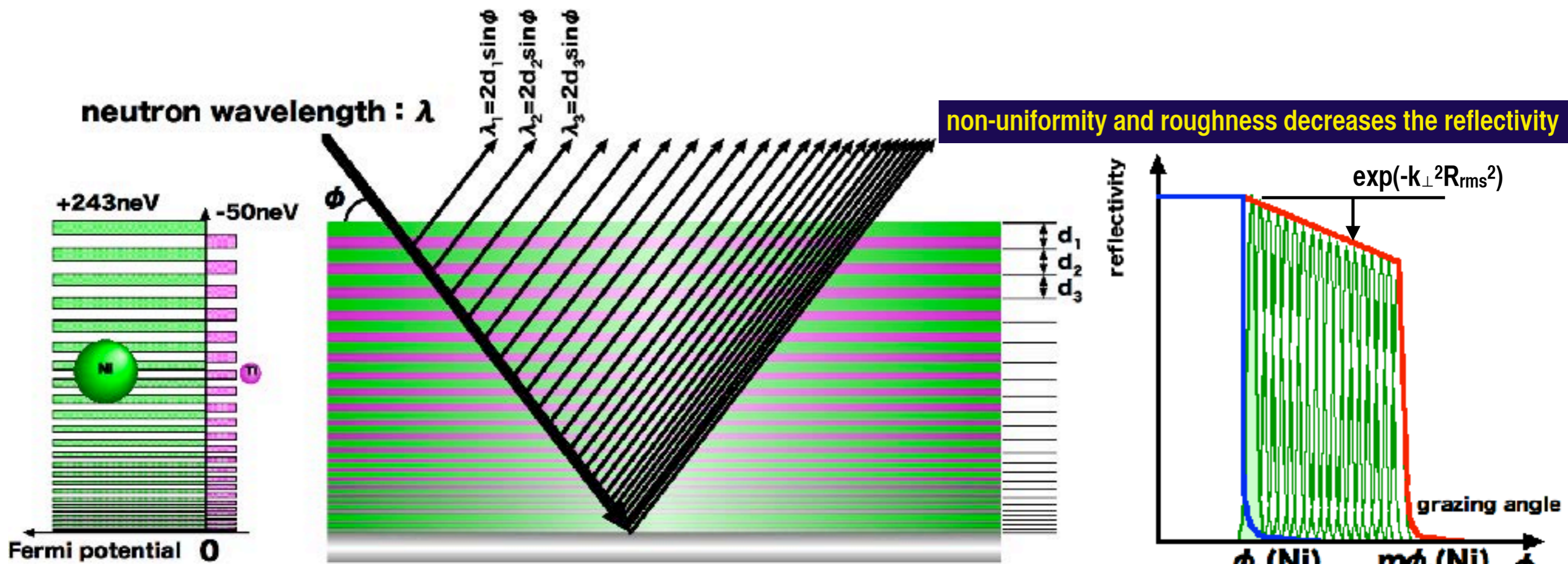
Multilayer Mirror



$$\frac{\phi_c(\text{Ni})}{\lambda_n} = 1.7 [\text{mrad } \text{\AA}^{-1}]$$

$$v_{\perp}(\text{Ni}) = 7 \text{ m/s}$$

Supermirror

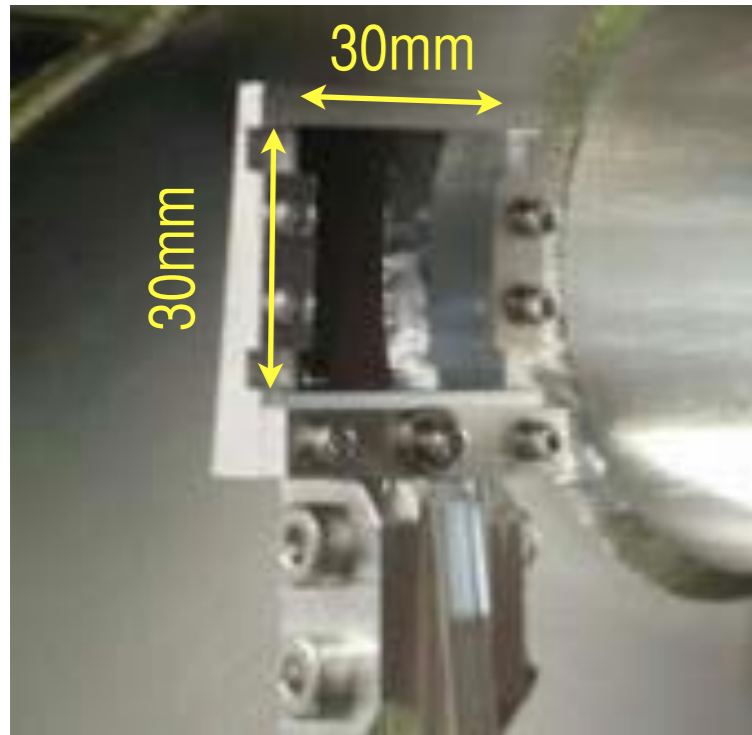


$$\frac{\phi_c(\text{Ni})}{\lambda_n} = 1.7 [\text{mrad } \text{\AA}^{-1}]$$

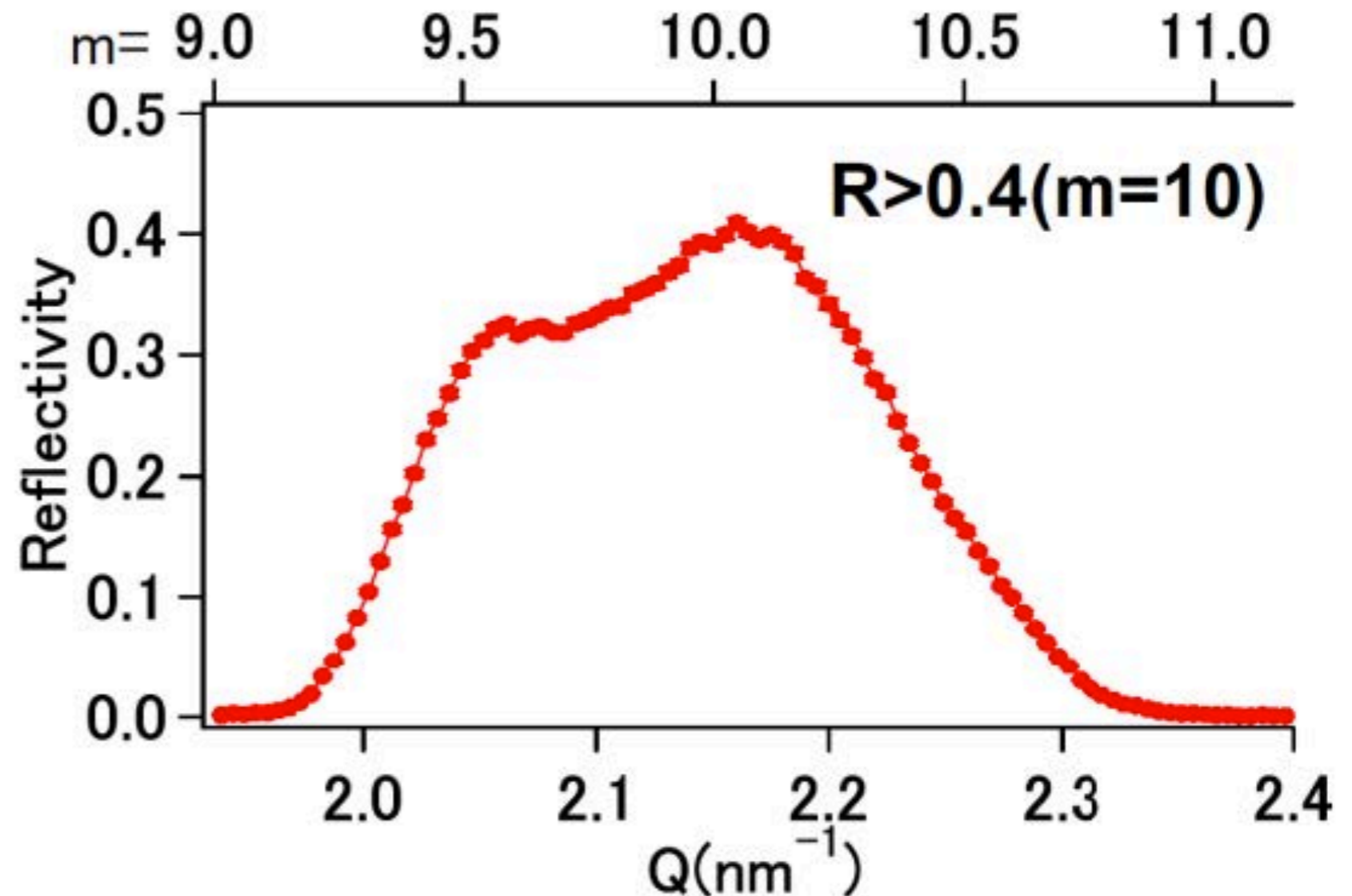
$$v_{\perp}(\text{Ni}) = 7 \text{ m/s}$$

$$m = \frac{\phi_c}{\phi_c(\text{Ni})} = \frac{v_{\perp}}{v_{\perp}(\text{Ni})}$$

Quadruple-stack Multilayer $m=10$ the highest m -value ever realized



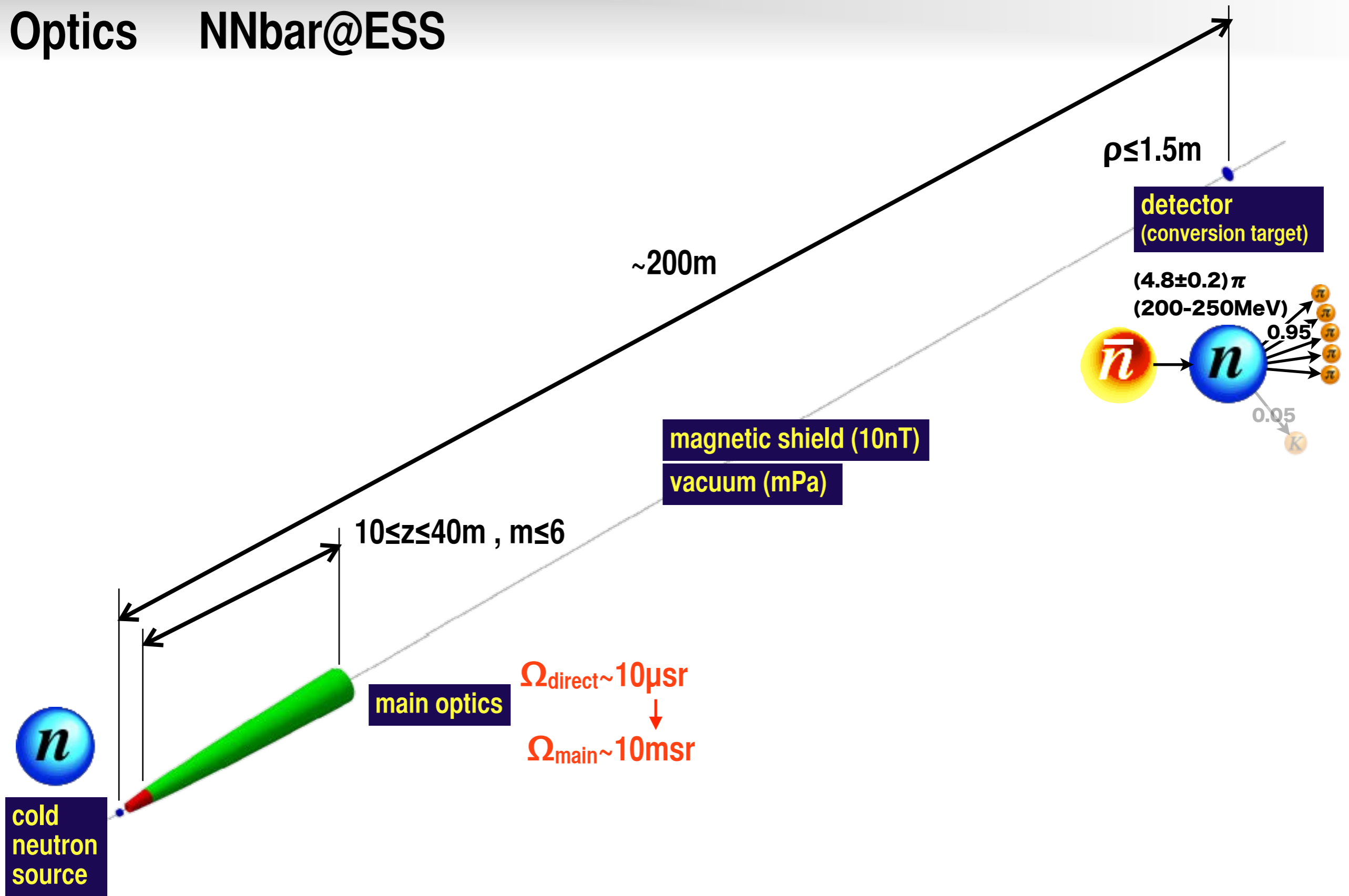
$m=10$ NiC/Ti wide-band monochromator



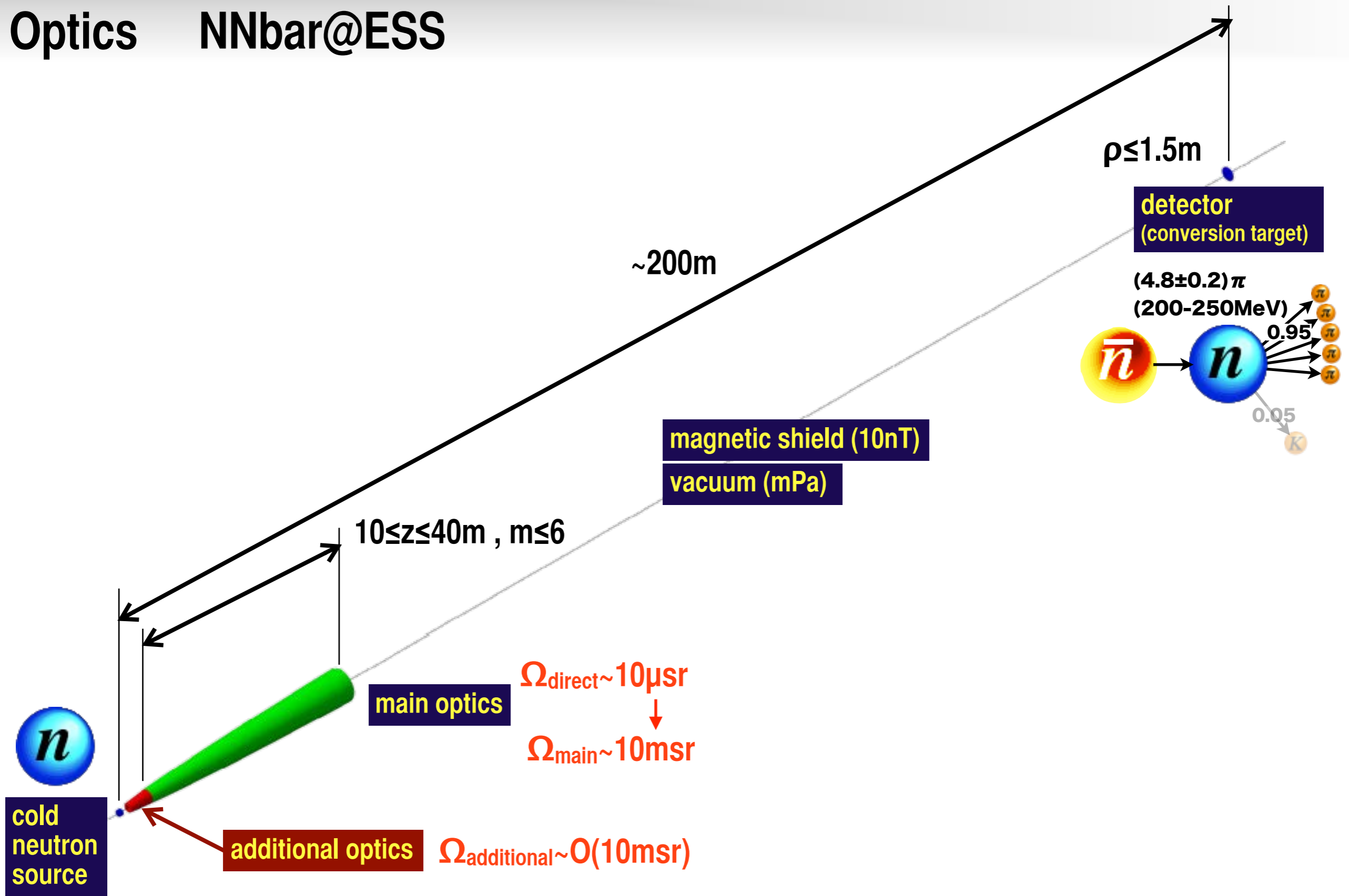
85060 bilayers in total = $4 \times (10336 + 10929)$ bilayers
quadruple-stack of double-sided multilayer mirrors

baseline optics

Optics NNbar@ESS



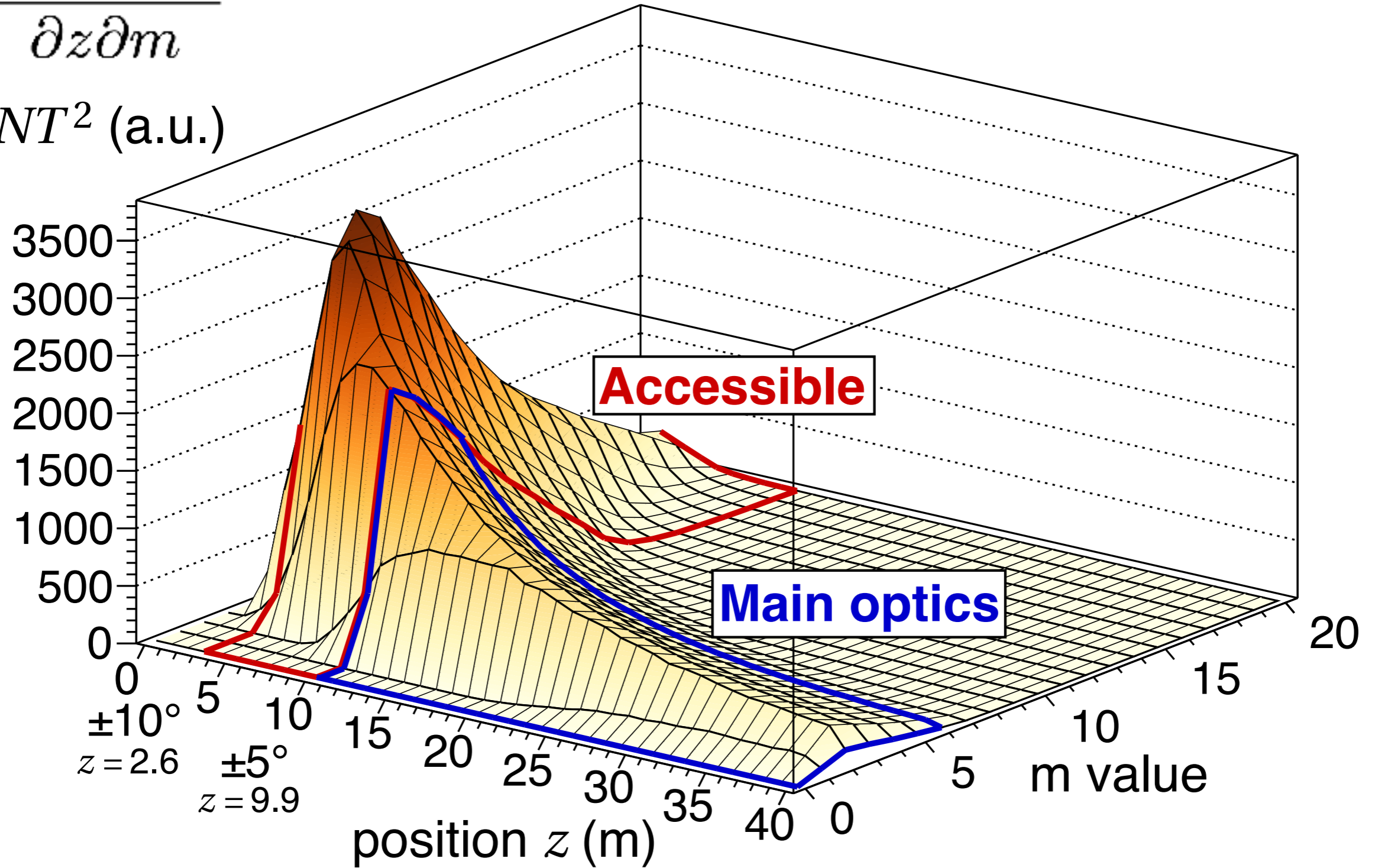
Optics NNbar@ESS

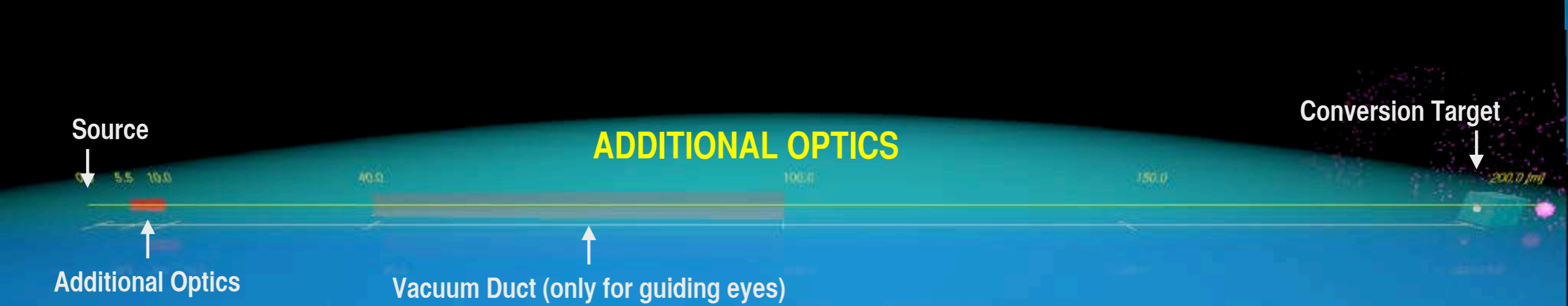
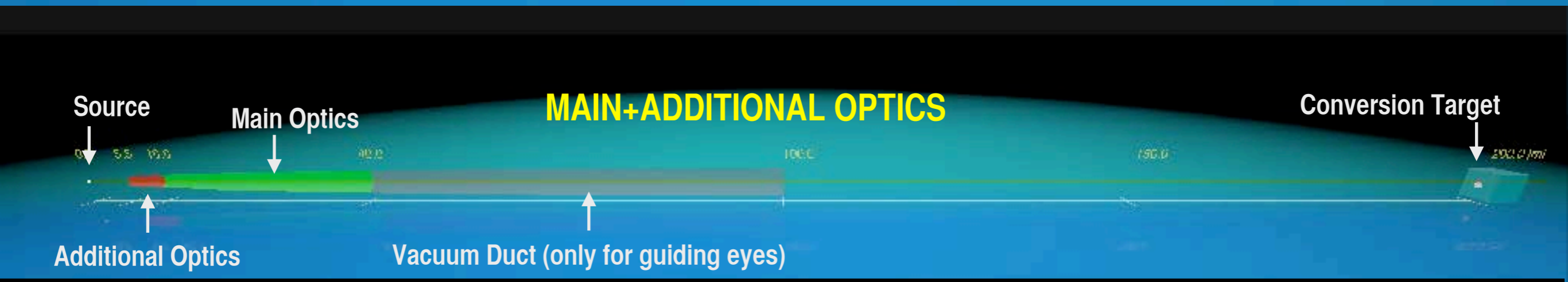
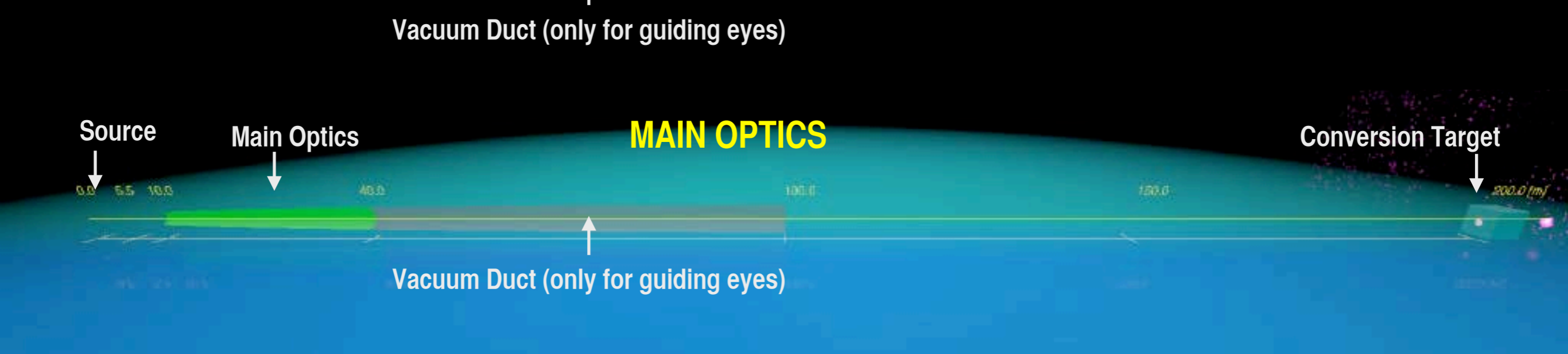
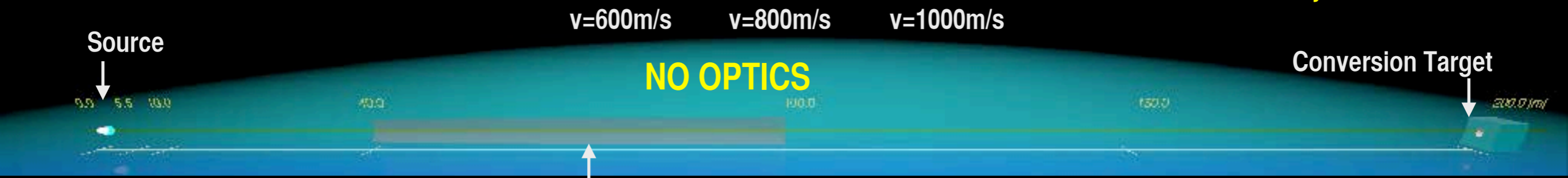


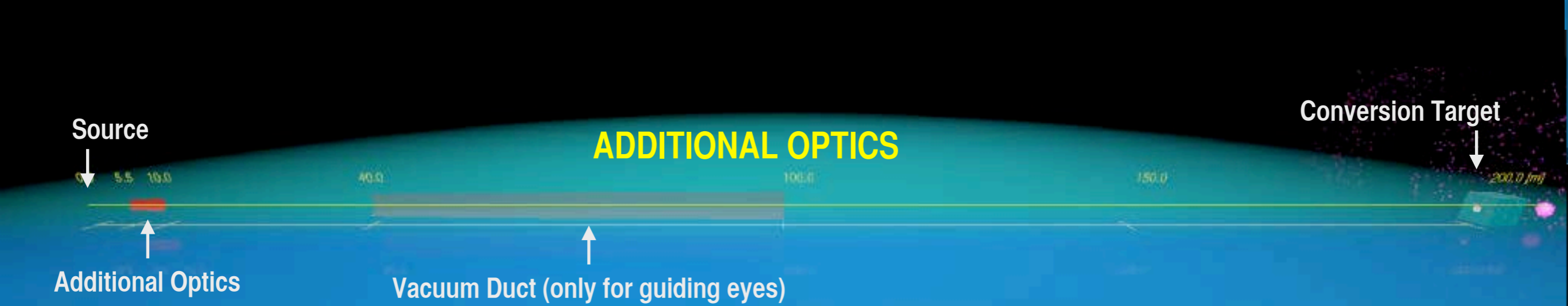
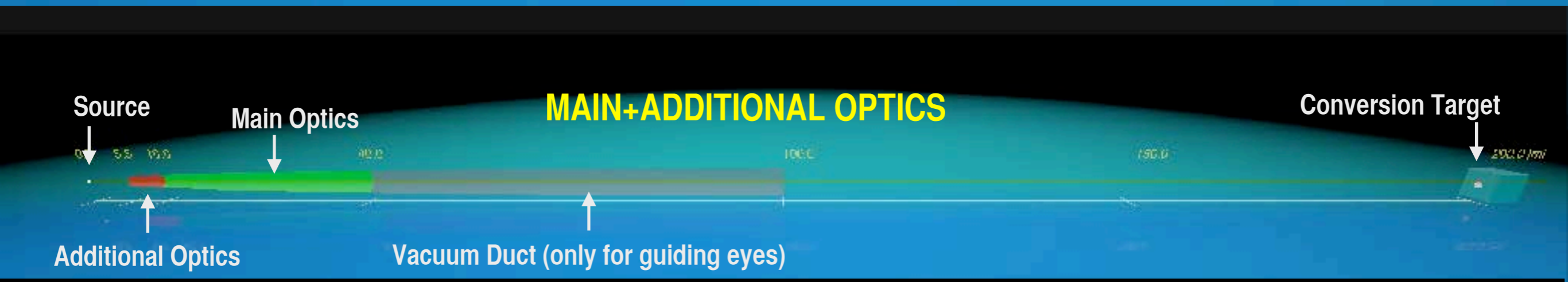
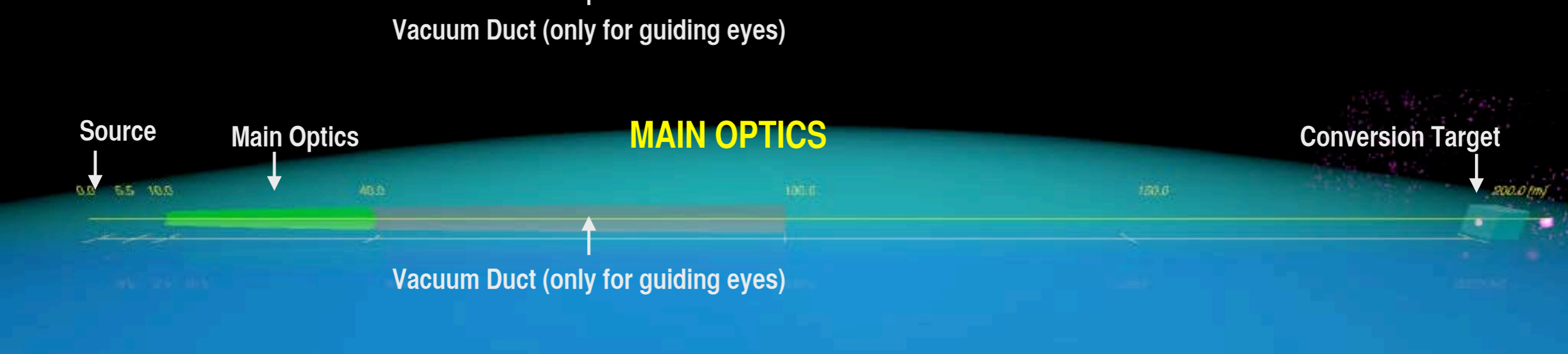
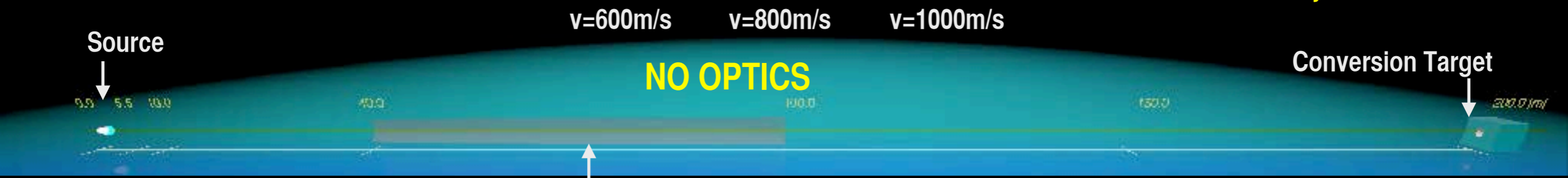
Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$

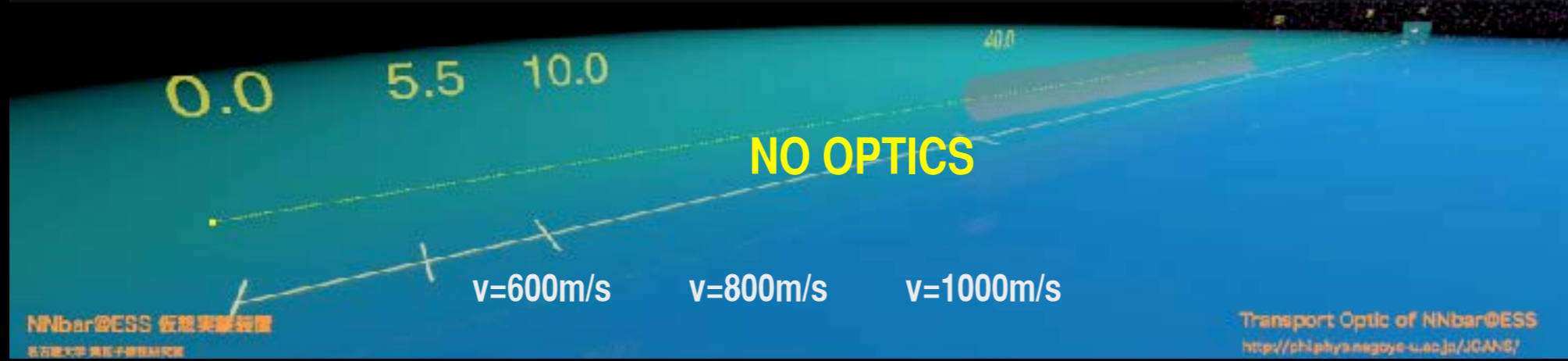
NT² (a.u.)



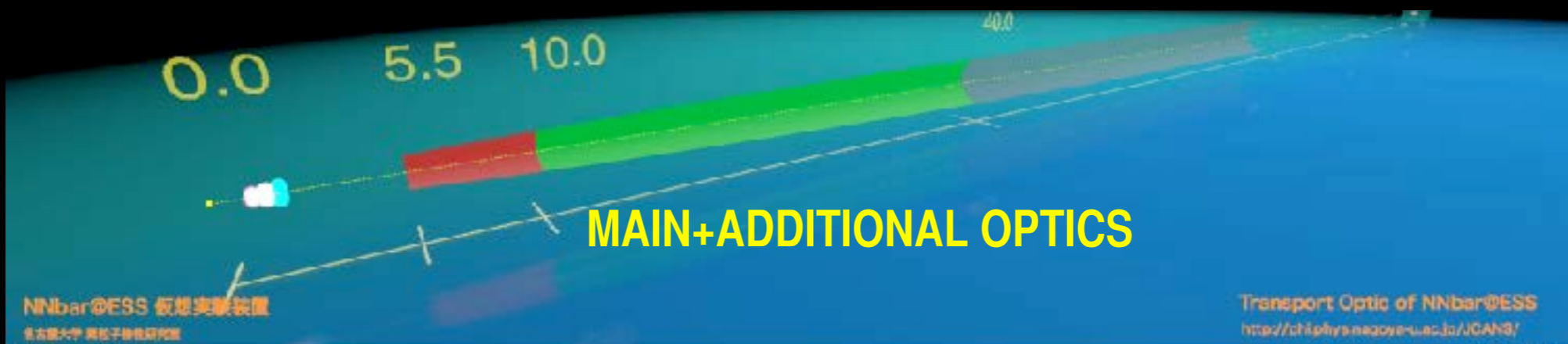
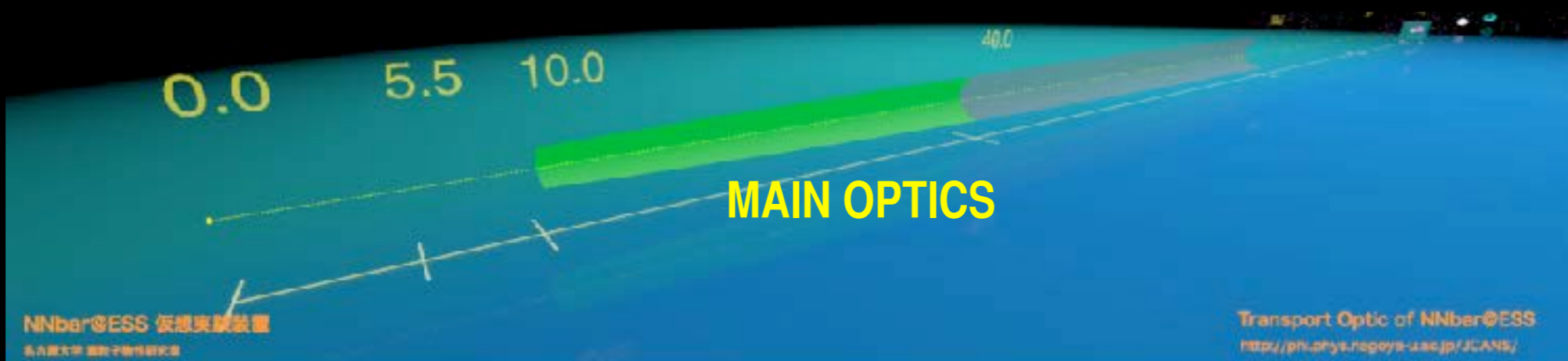
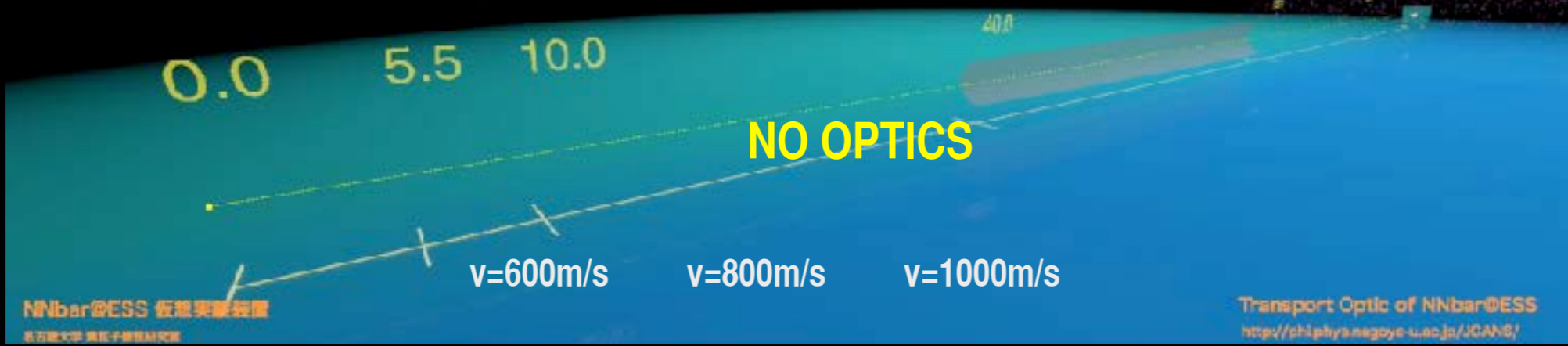




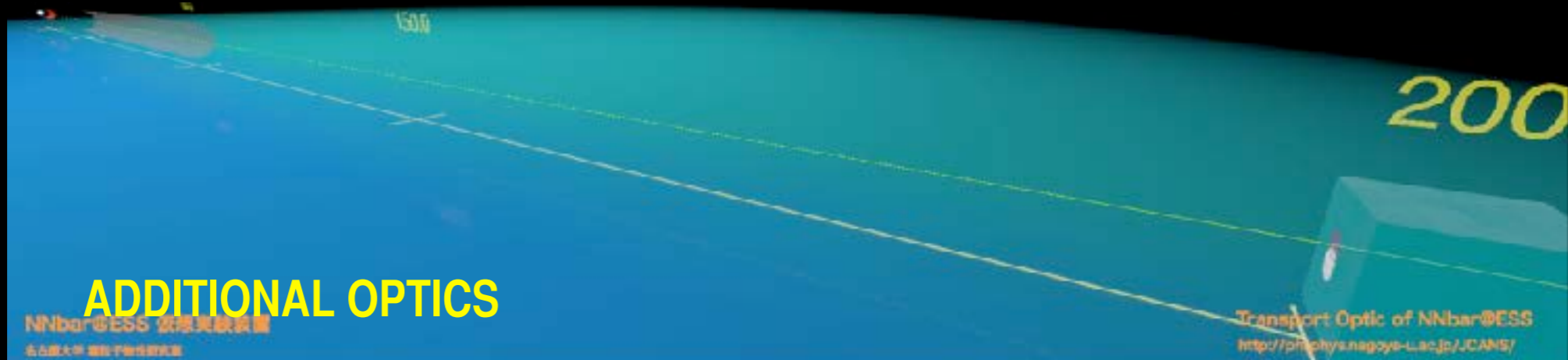
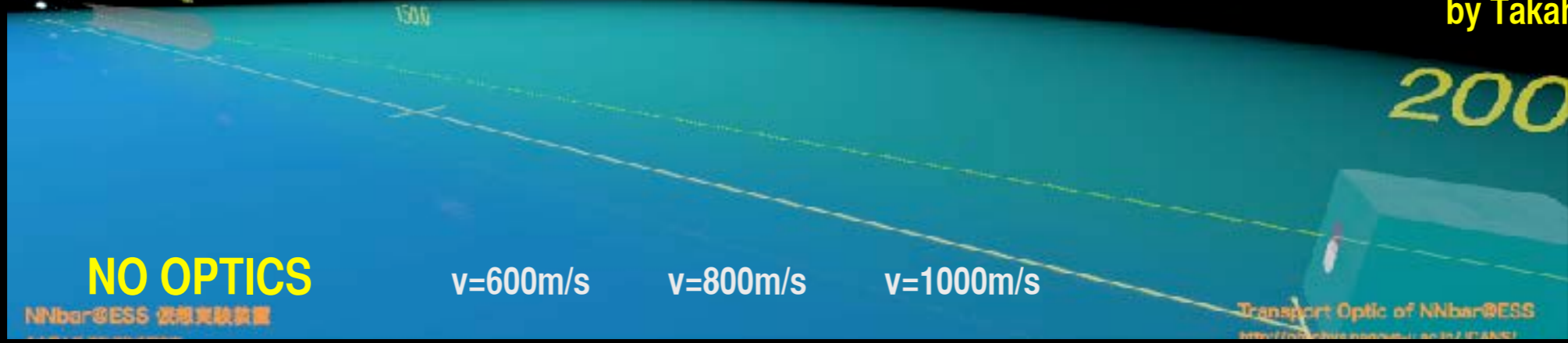
Viewing from the Source



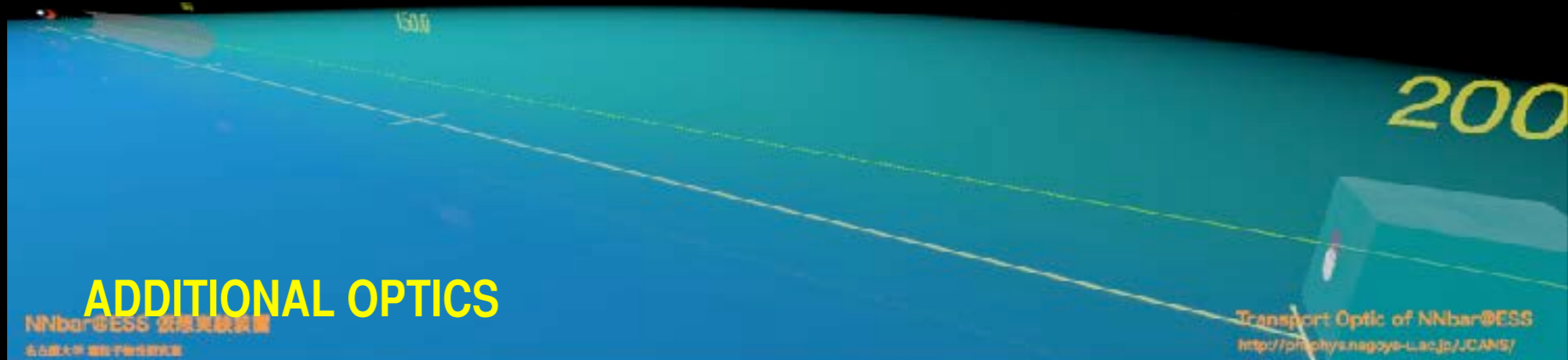
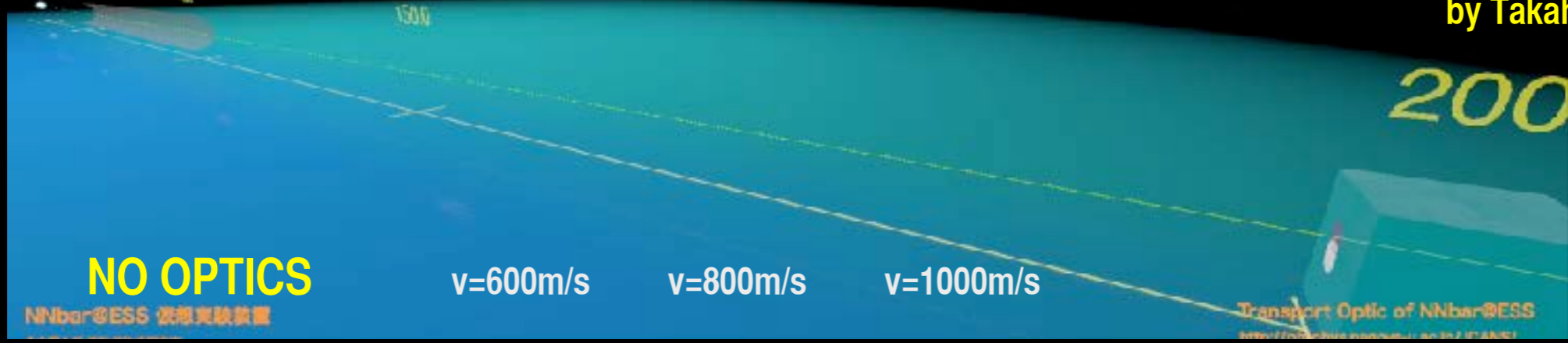
Viewing from the Source



Viewing from the Detector

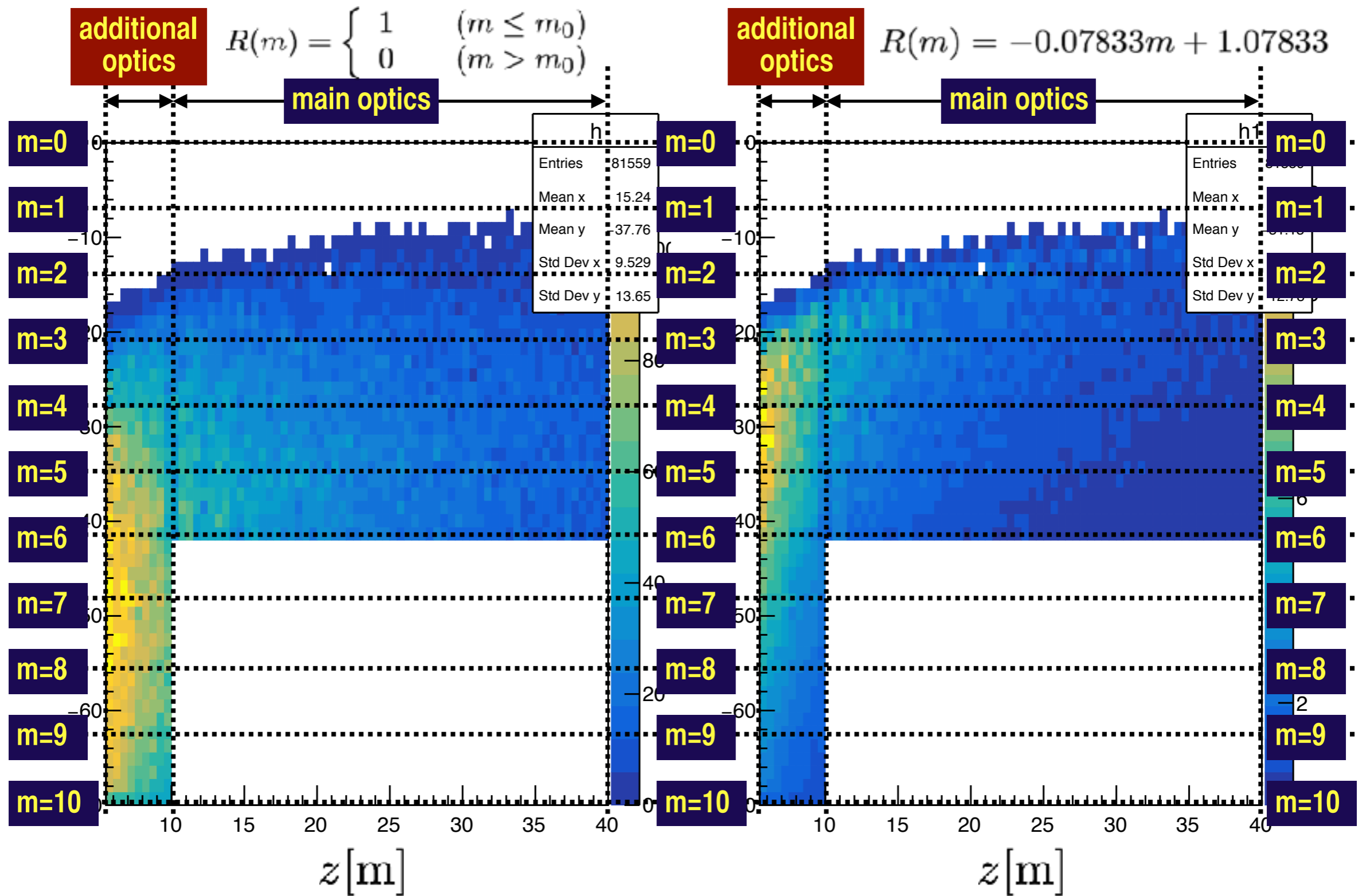


Viewing from the Detector

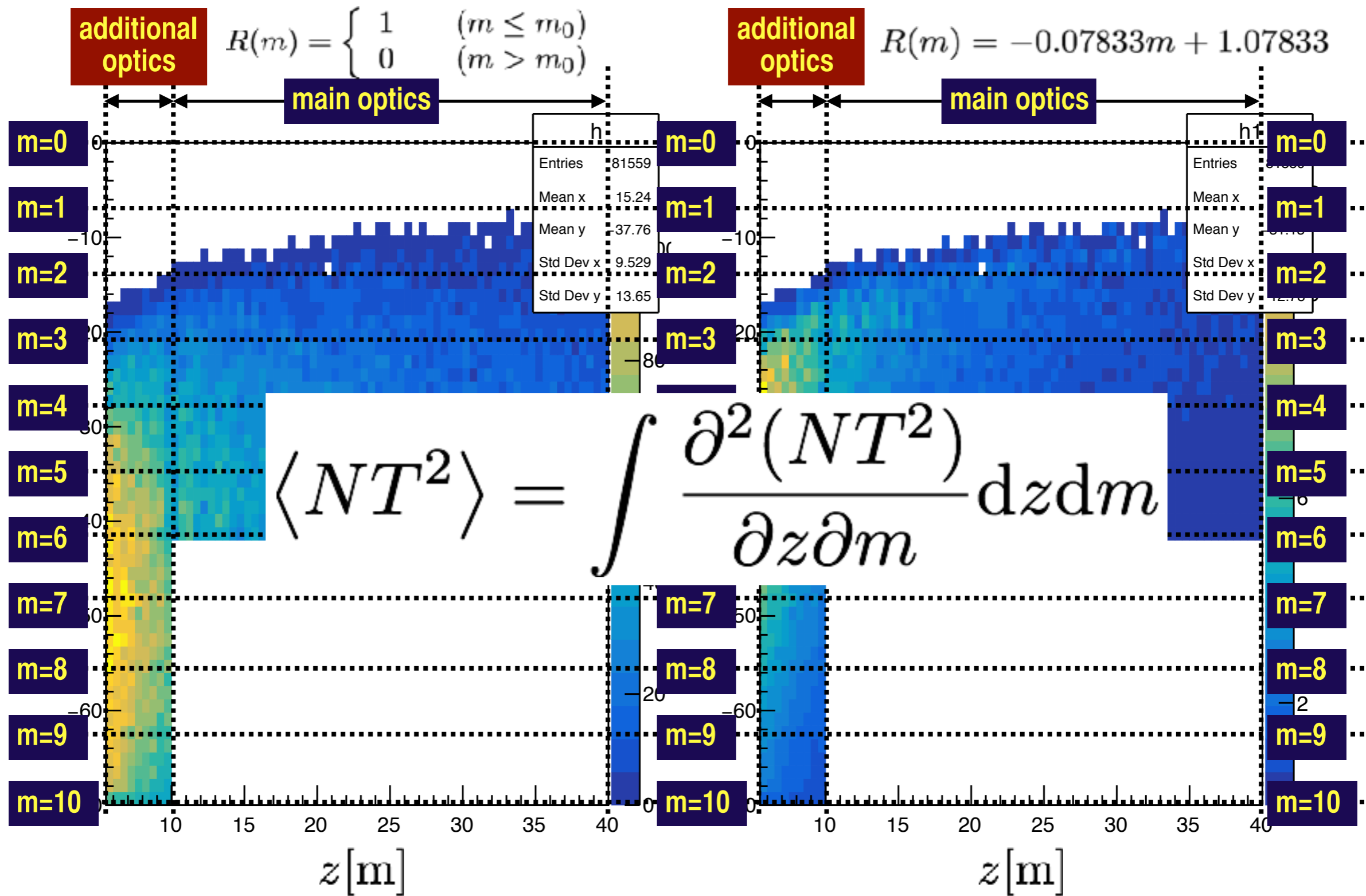


Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$



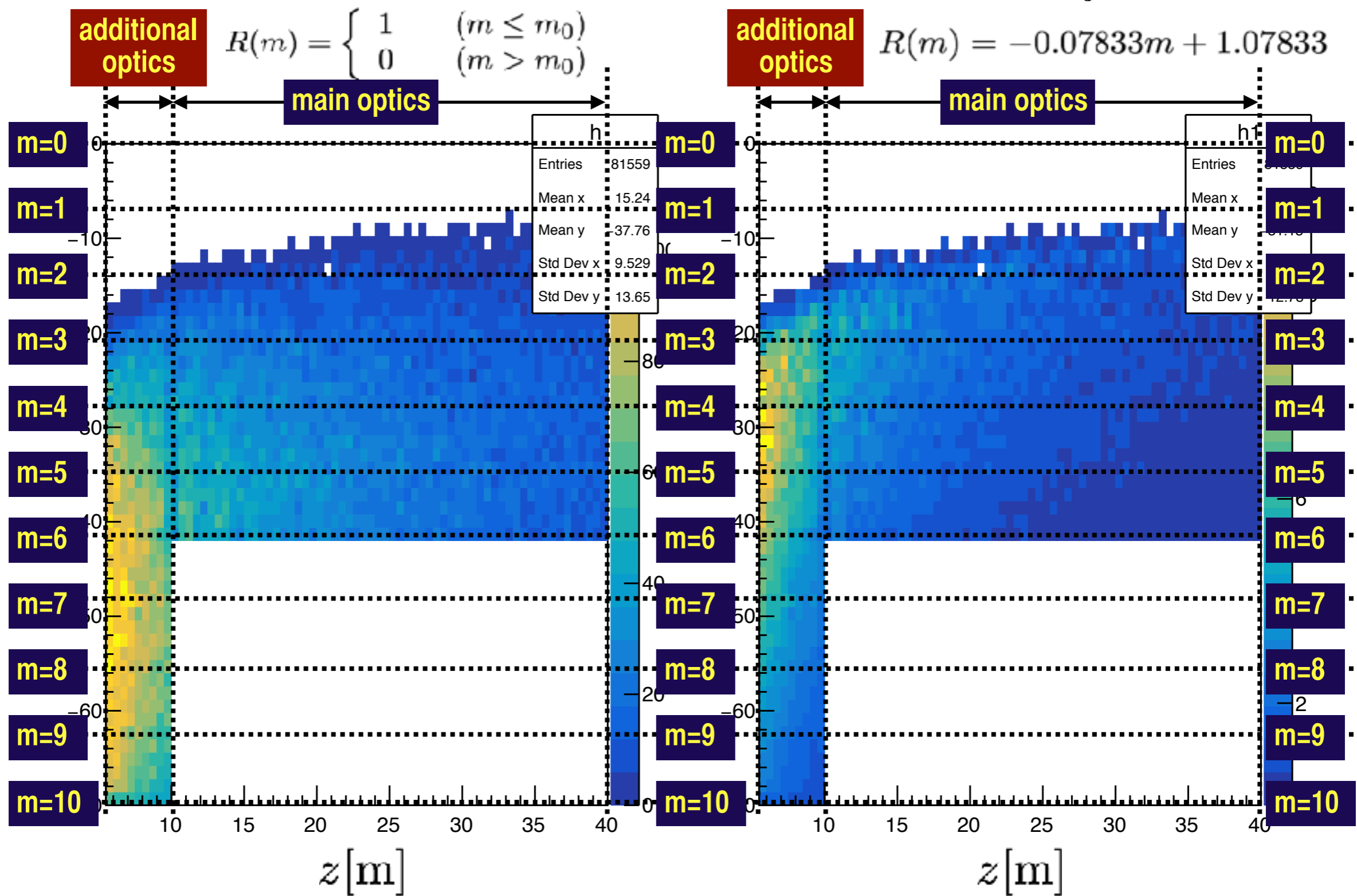
Map of Figure-Of-Merit (NT²) $\frac{\partial^2(NT^2)}{\partial z \partial m}$



Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$

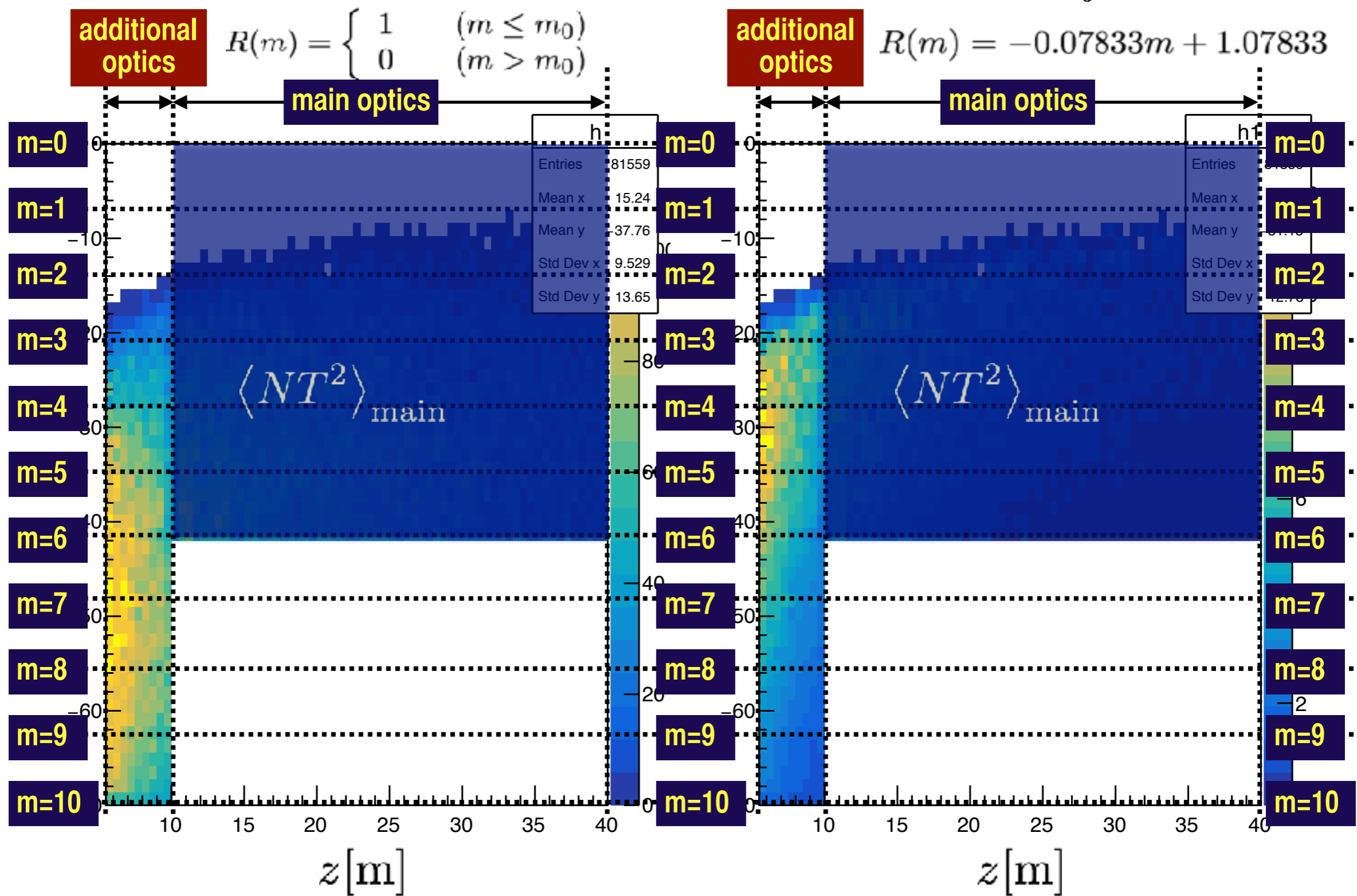
$$\langle NT^2 \rangle = \int \frac{\partial^2(NT^2)}{\partial z \partial m} dz dm$$



Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$

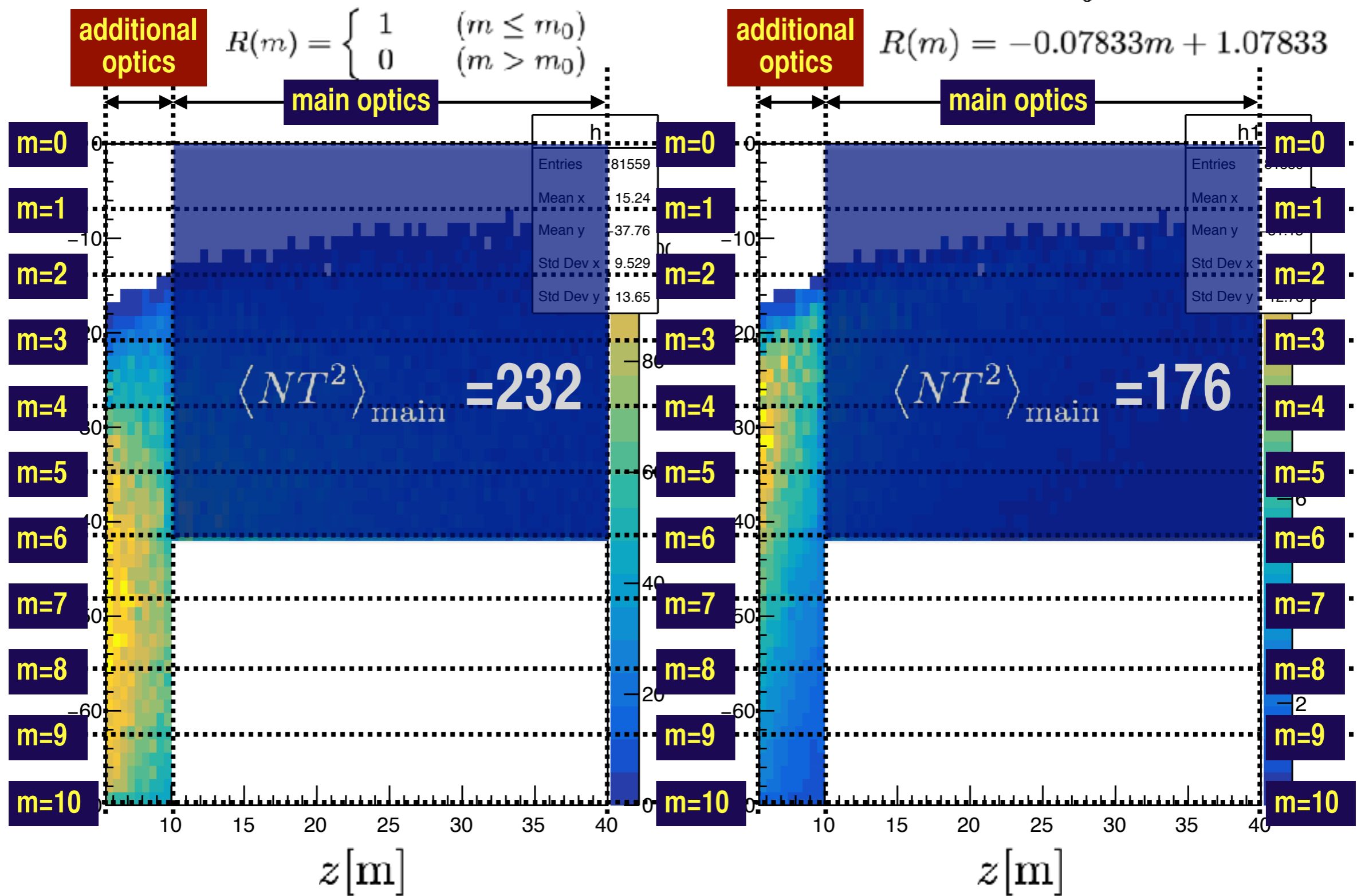
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Map of Figure-Of-Merit (NT²)

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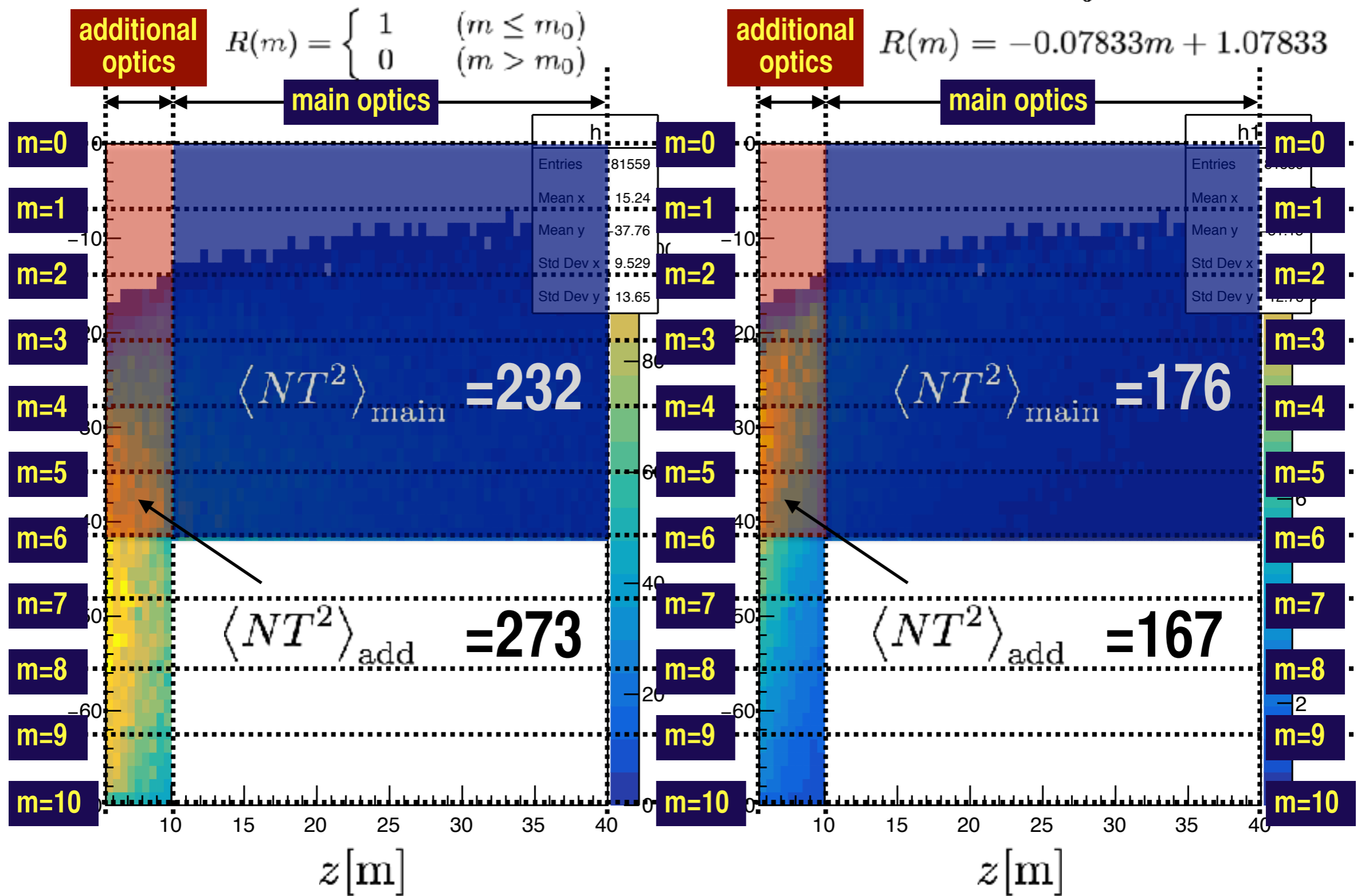
$$\langle NT^2 \rangle = \int \frac{\partial^2(NT^2)}{\partial z \partial m} dz dm$$



Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$

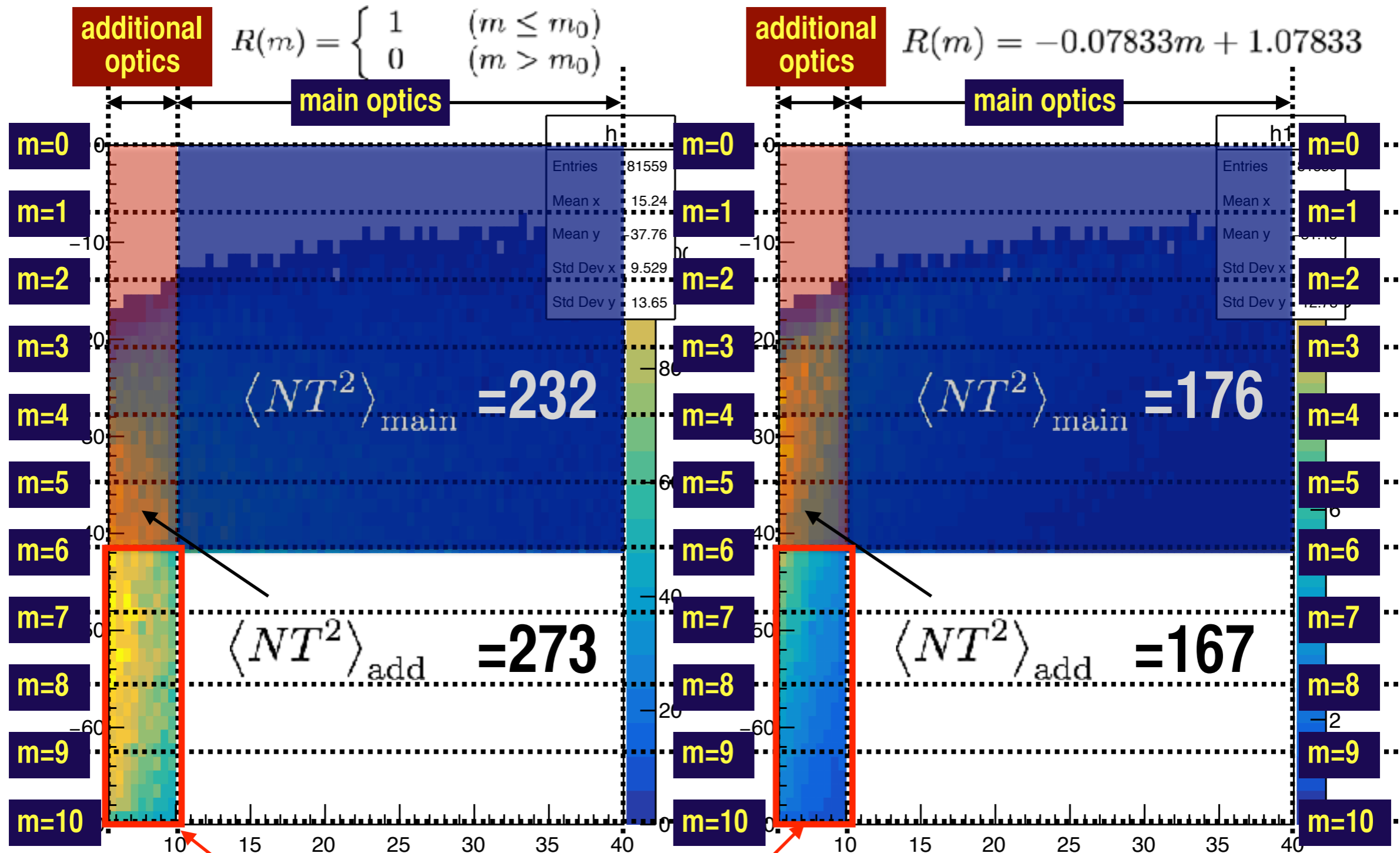
$$\langle NT^2 \rangle = \int \frac{\partial^2(NT^2)}{\partial z \partial m} dz dm$$



Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$

$$\langle NT^2 \rangle = \int \frac{\partial^2(NT^2)}{\partial z \partial m} dz dm$$



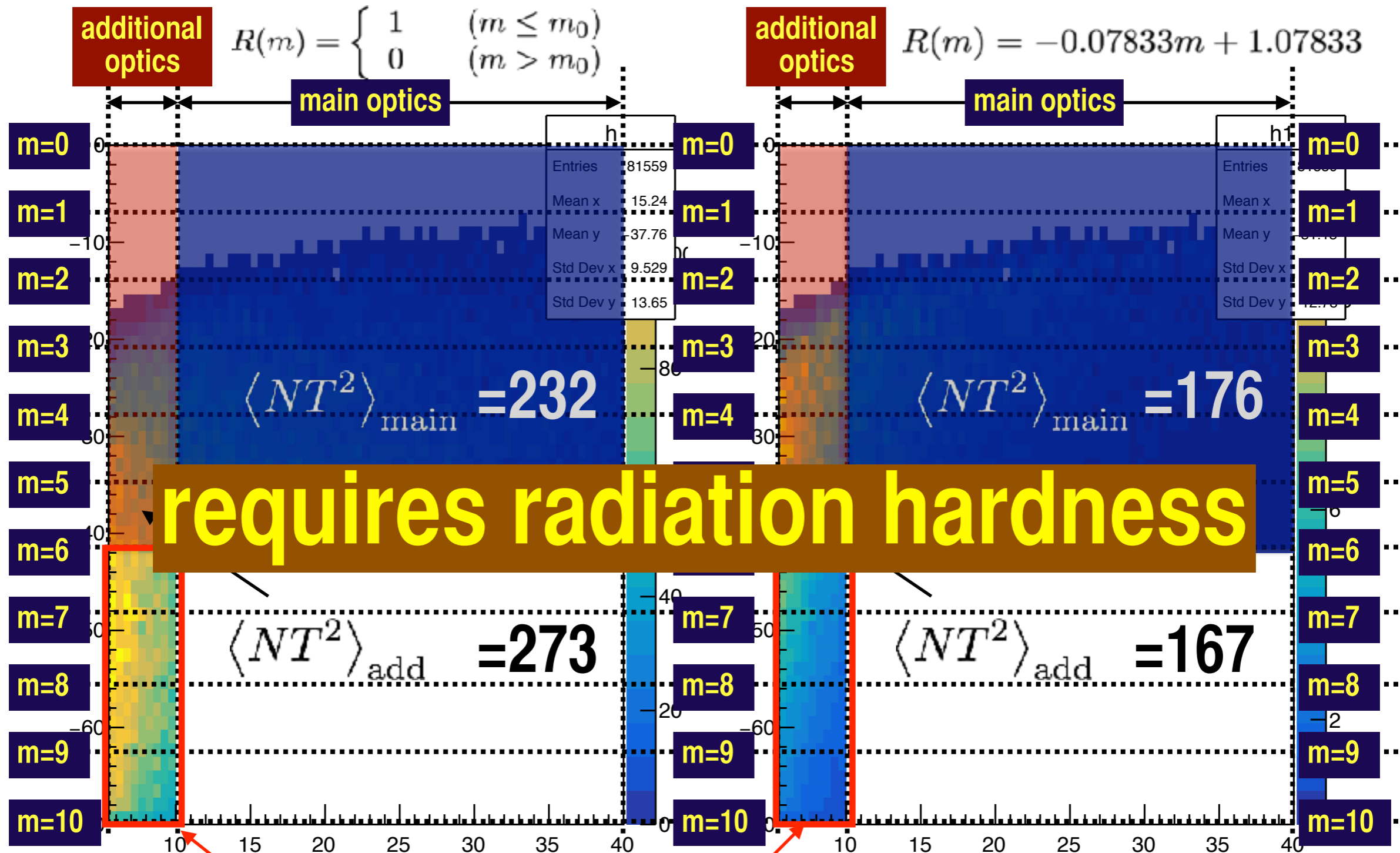
Most of neutrons in this region are fast, they do not contribute to NT² very much. The contribution of the region of 6 ≤ m ≤ 10 is not very large.



Map of Figure-Of-Merit (NT²)

$$\frac{\partial^2(NT^2)}{\partial z \partial m}$$

$$\langle NT^2 \rangle = \int \frac{\partial^2(NT^2)}{\partial z \partial m} dz dm$$



requires radiation hardness

Most of neutrons in this region are fast, they do not contribute to NT² very much. The contribution of the region of 6 ≤ m ≤ 10 is not very large.



Metal Substrate Multilayer Mirror

Yutaka YAMAGATA*, Jiang GUO*, Shin-ya MORITA*, Jun-ichi KATO*, Katsuya HIROTA*, Yoshie OTAKE**,
Atsushi TAKETANI**, Sheng WANG**, Shin TAKEDA****, Masahiro HINO*** and Michihiro FURUSAKA****

*Ultrahigh Precision Optics Technology Team, RIKEN Center for Advanced Photonics (RAP), RIKEN, Japan
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**Neutron Beam Technology Team, RIKEN Center for Advanced Photonics, RIKEN, Japan

***Kyoto University Research Reactor Institute

**** Hokkaido University

Metal-Substrate Multilayer Mirror (catalogued by J-NOP Inc.)

Aluminum substrate with amorphous Ni-P plated surface

Advantages:

- Easy handling and fixture
- Robust and resistant to heat shock and radiation damage
- Very low surface roughness
- Usable as m=1 mirror without supermirror coating
- **Full numerical control:** flat surface, 1-D ellipsoidal surface, 2-d elliptic surface and other complicated optics
- **Precision multiple-segment alignment technology enables large-scale mirror fabrication**

cf.) This technique can be applied to stainless steel substrate, glass substrate, ..., if necessary.

Neutron Focusing Mirror with Metallic Substrate



Neutron Mirrors have been conventionally manufactured using brittle materials like glass or silicon, but handling, precision of such mirrors were not satisfactory. RIKEN and J-NOP have developed a new technology of neutron focusing mirrors using metallic substrate with easier handling, high precision and multiple segment capabilities.

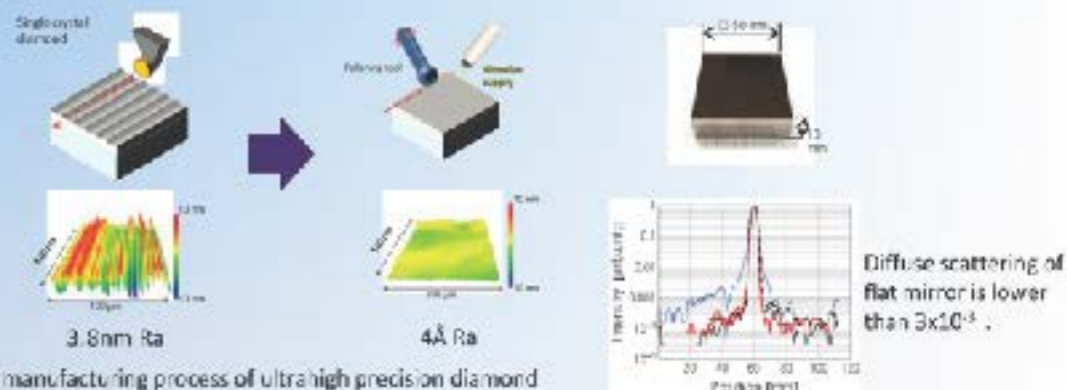


A 550mm ellipsoidal mirror prototype with two segments

The new technology mirror uses aluminum based substrate and amorphous Ni-P (Nickel Phosphate) plated surface.

Advantages:

- Easy handling and fixture using metallic substrate.
- Robust and resistant to heat shock and radiation damage.
- Very low surface roughness by amorphous Ni-P plating.
- It can be used as 1Qc mirror without super-mirror coating.
- Various types of super-mirror coating is available.
- Flat surface, 1-D ellipsoidal surface, 2-d elliptic surface and other complicated optics can be manufactured.
- Precision Multiple-segment alignment technology enables large-scale mirror fabrication.



New manufacturing process of ultrahigh precision diamond cutting with subsequent super-smooth polishing enables angstrom surface roughness with rather rapid manufacturing speed.



Prototype of small 2-D ellipsoidal mirror



Japan Neutron Optics Inc.

Riken-Wako Incubation Plaza 407
Minami 2-3-13, Wako, Saitama, 351-0104, Japan
e-mail: jnop-info@j-nop.com
URL: <http://www.j-nop.com>

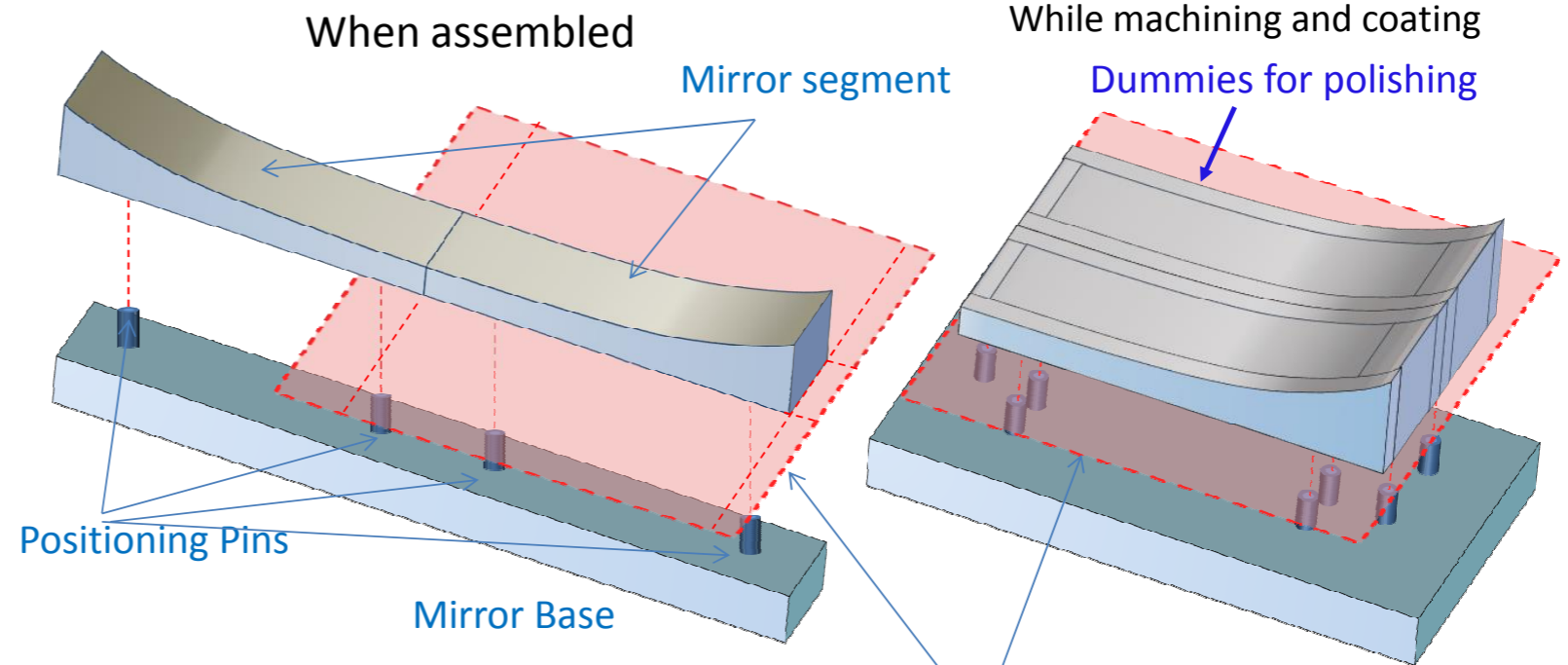
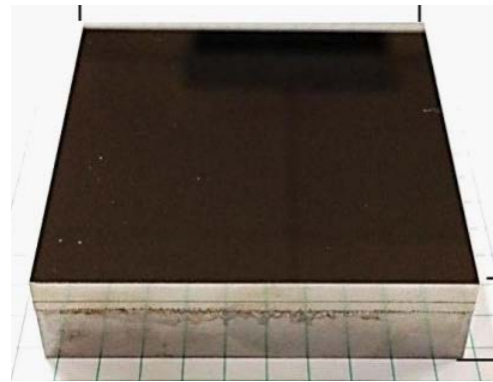
Neutron Optics



Fabrication method for multi-segmented mirror

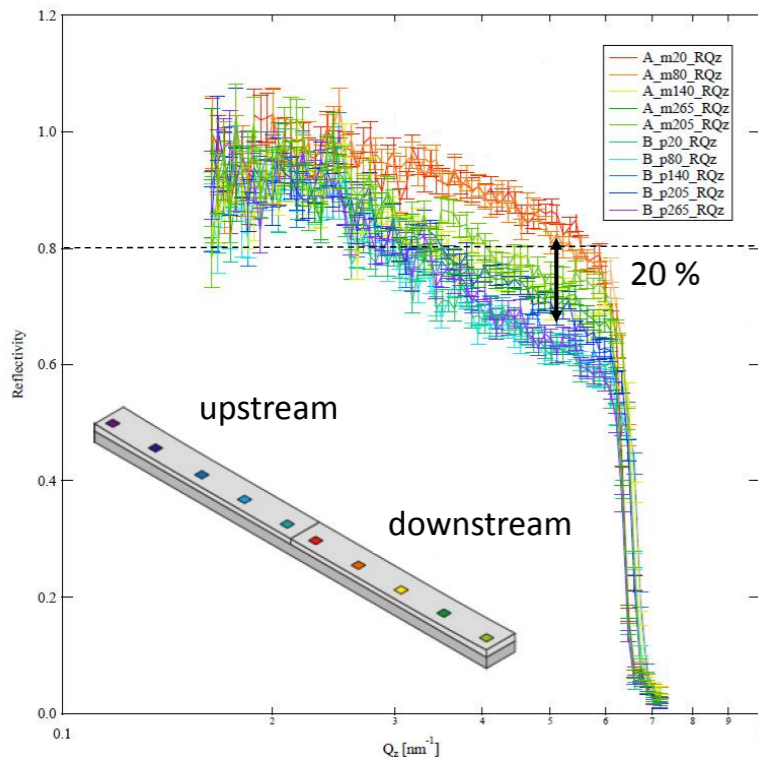


Metal substrate mirror

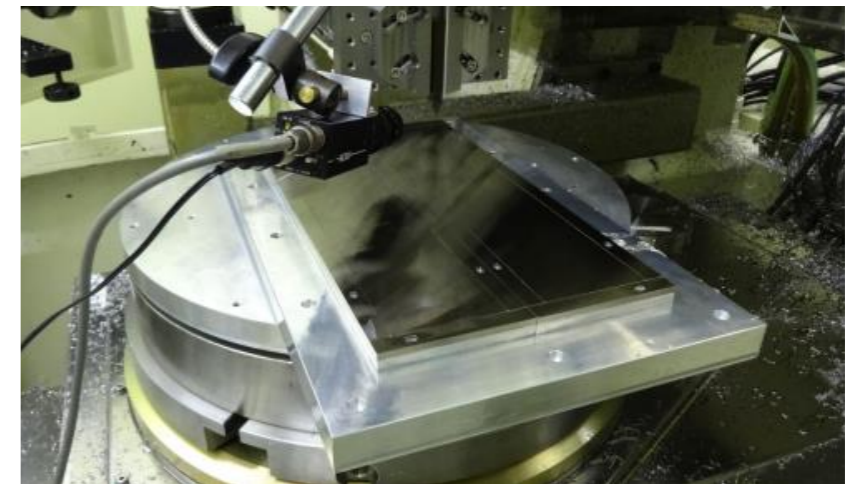


Alignment of mirror segments are controlled by positioning pins

Segment size is limited by coating chamber capacity.



- Reflectivity of several parts showed as high reflectivity as glass substrate mirrors
- Reflectivity decrease are due to surface contamination by polishing abrasives



• R&D in progress under the collaboration among PSI, RIKEN and KUR.

Summary 1

Additional optics doubles the FOM.

$$\langle NT^2 \rangle_{\text{main}} \sim \langle NT^2 \rangle_{\text{add}}$$

**If we use only the additional optics,
the flight-path radius can be reduced.**

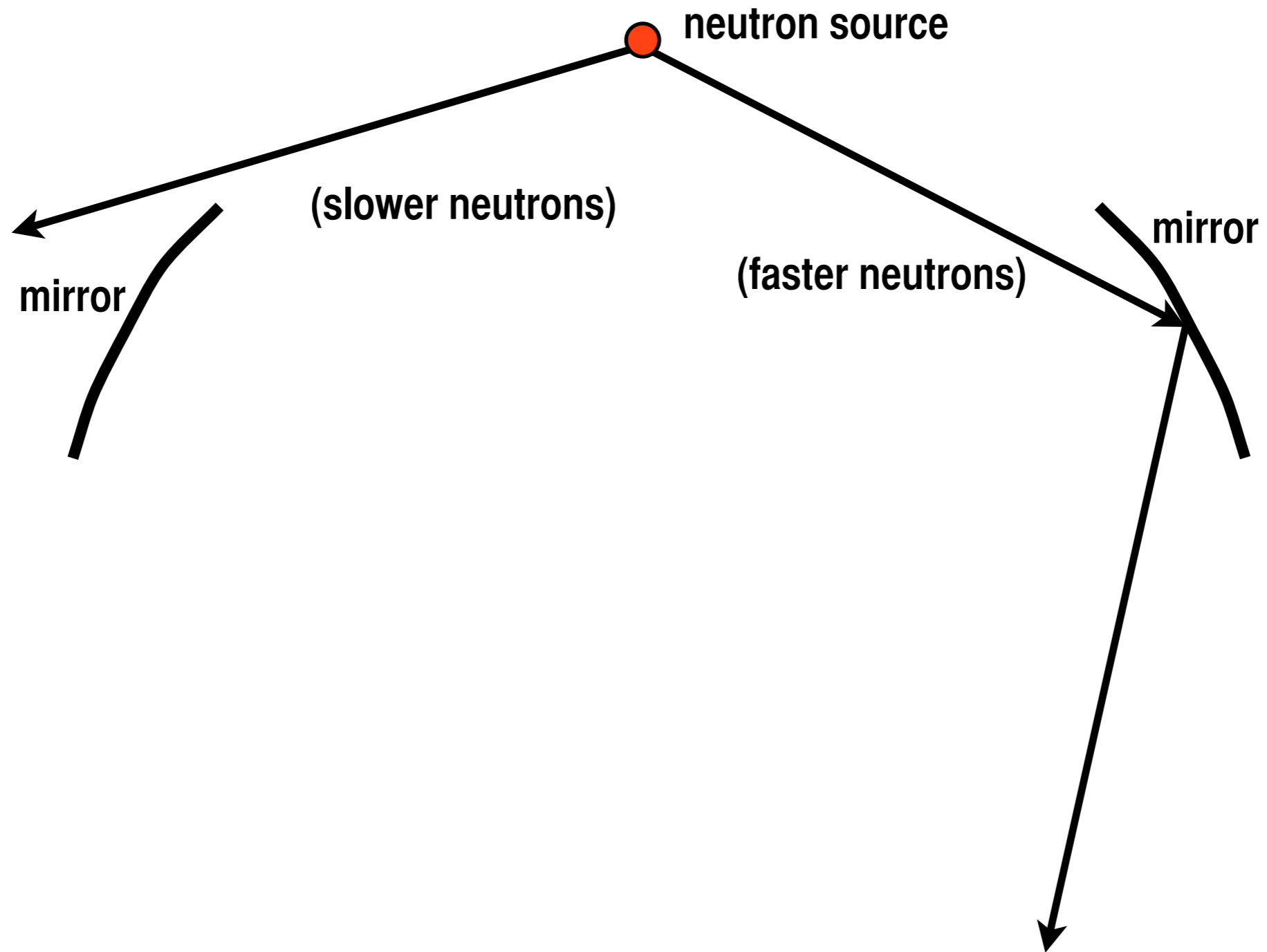
**a thinner vacuum tube
a smaller magnetic shield
cost effective**

a discussion for more acceptance

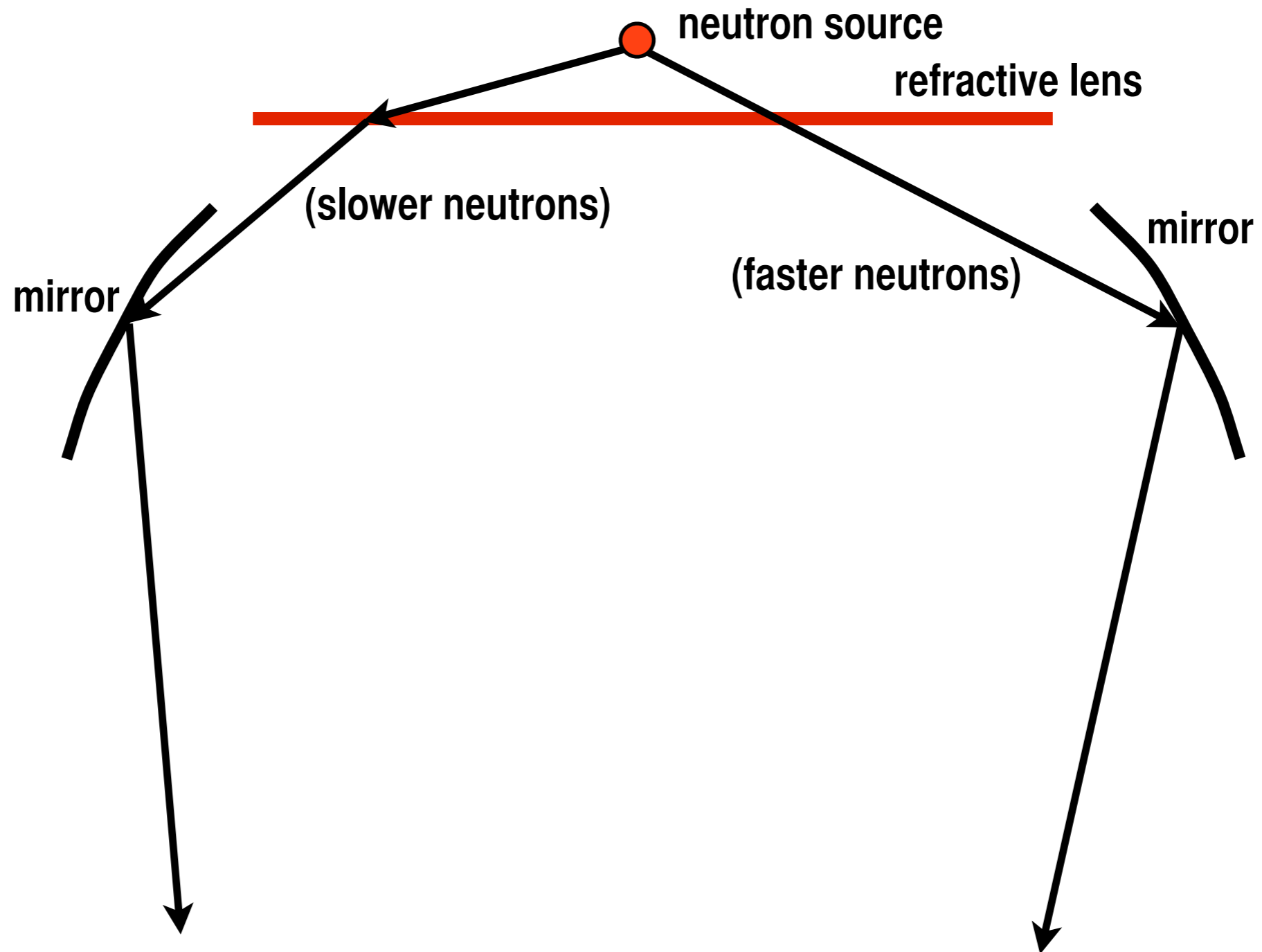
Auxiliary Optics

for an additional acceptance

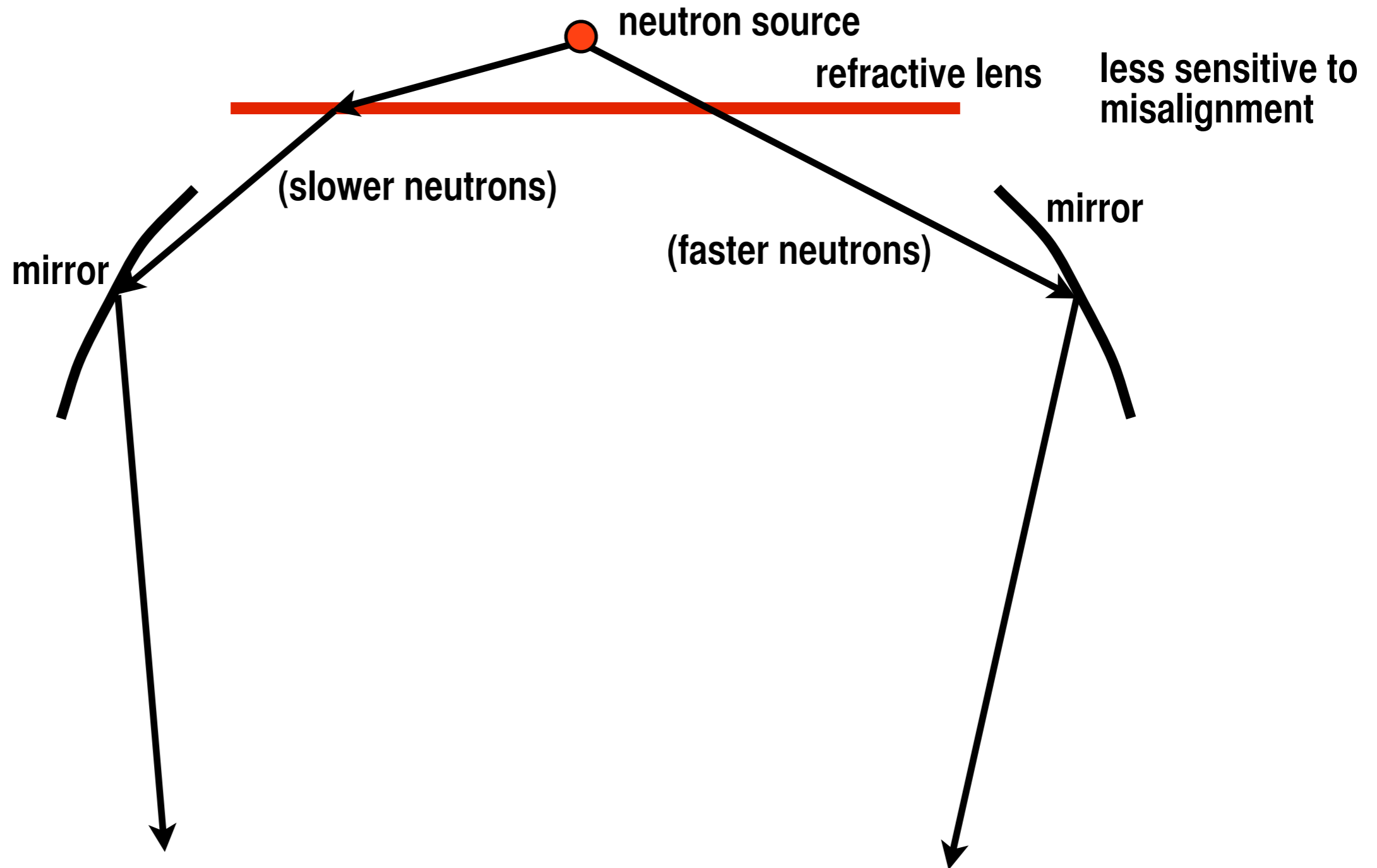
Refractive Lens for Enlarging Effective Acceptance



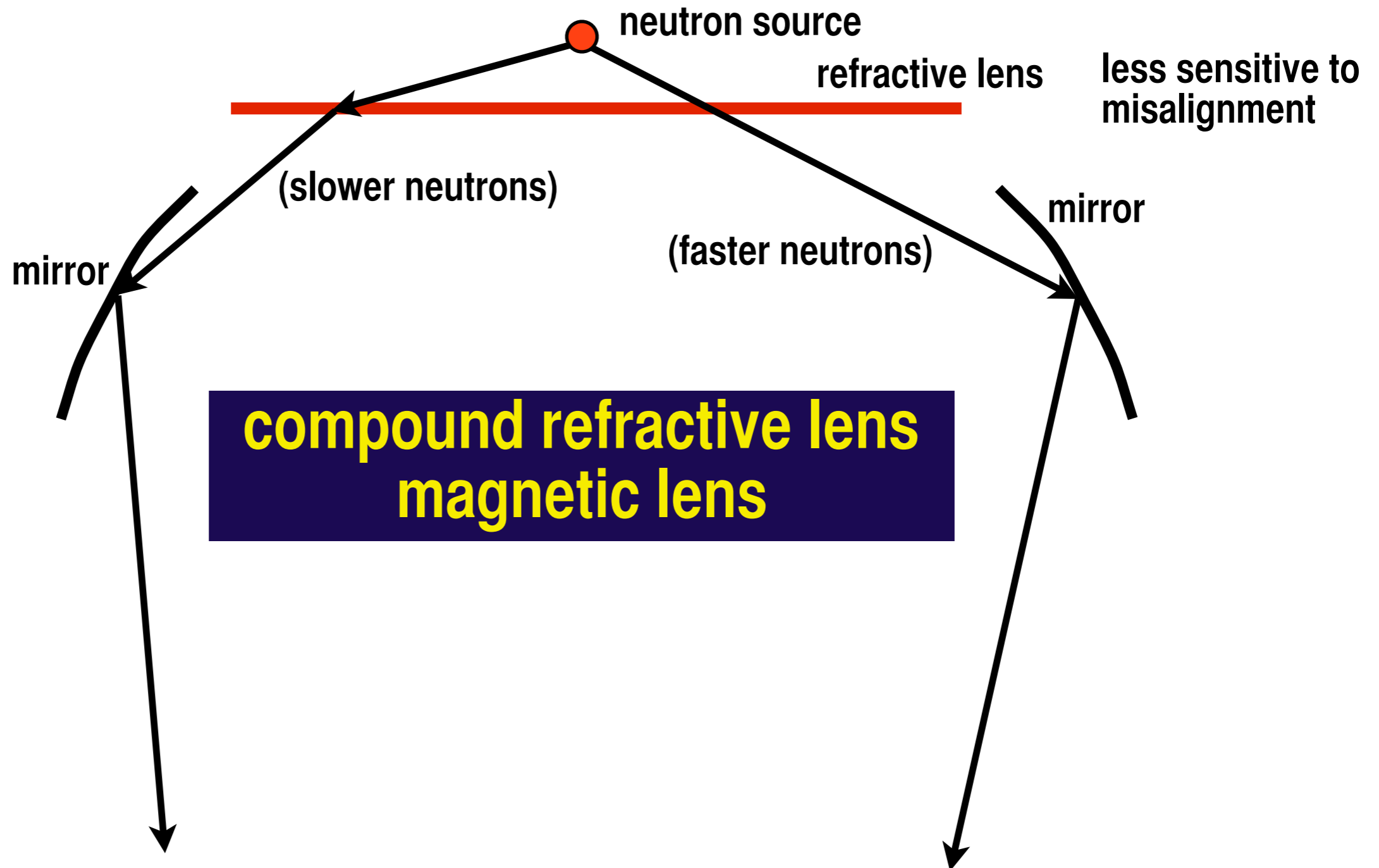
Refractive Lens for Enlarging Effective Acceptance



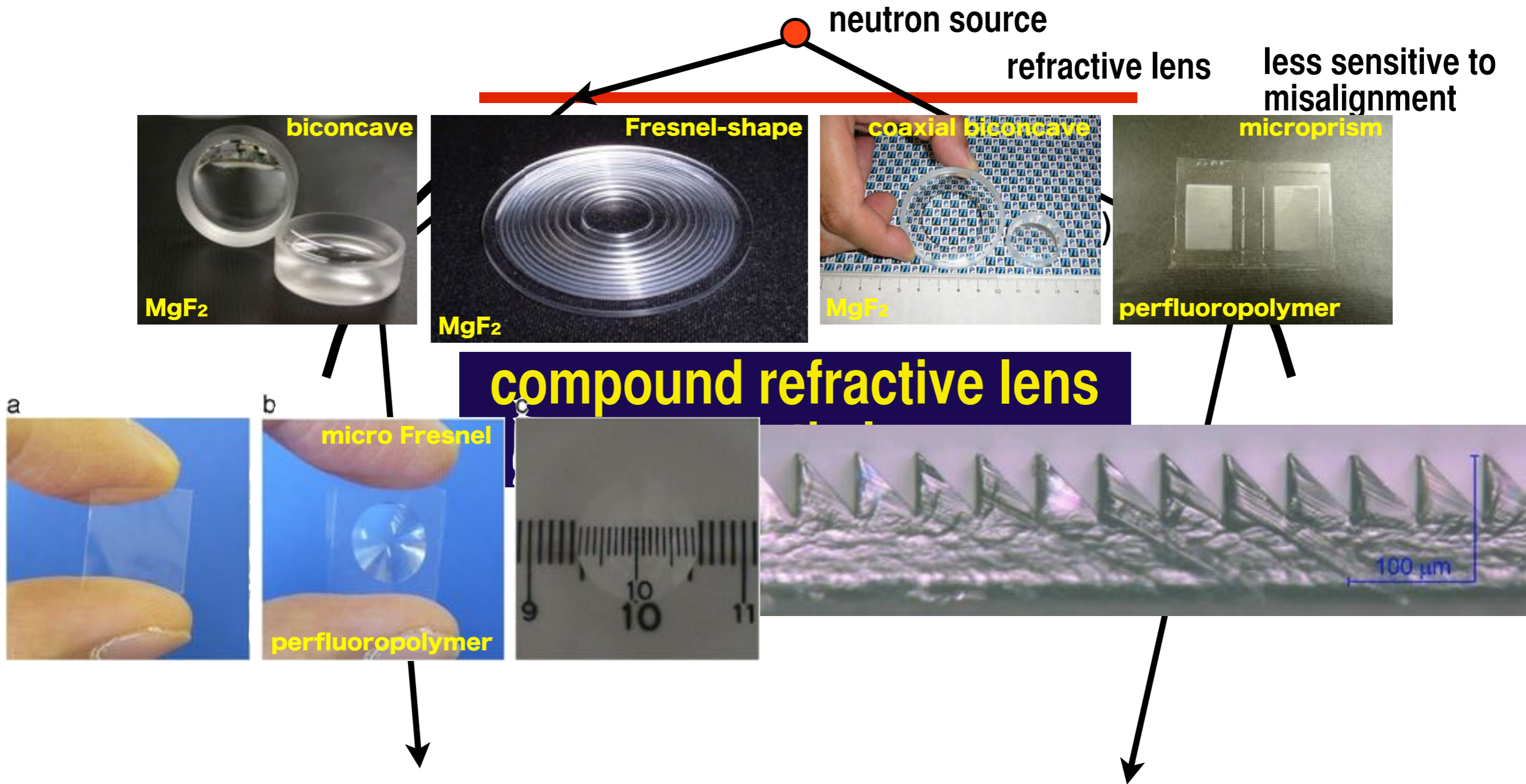
Refractive Lens for Enlarging Effective Acceptance



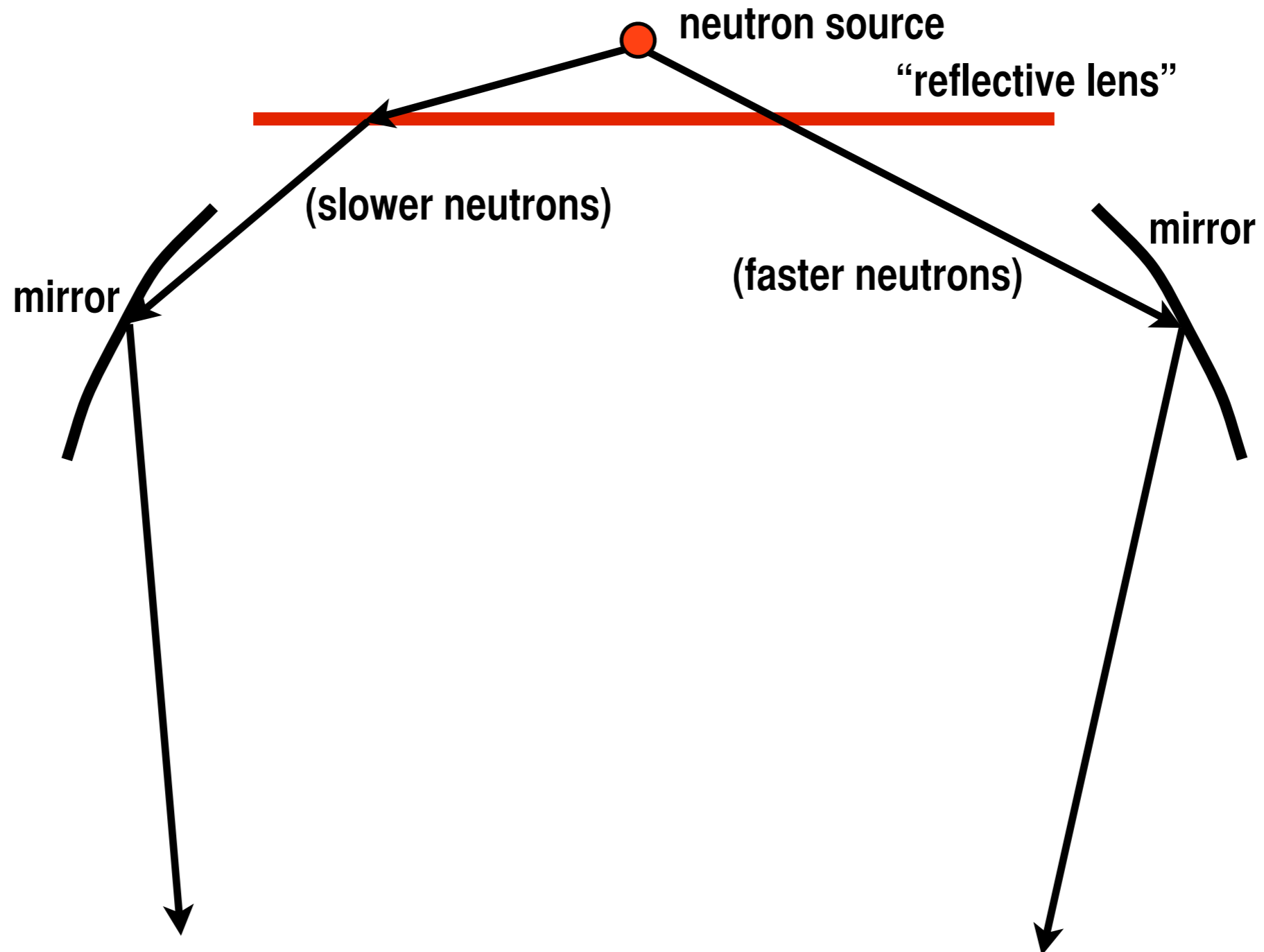
Refractive Lens for Enlarging Effective Acceptance



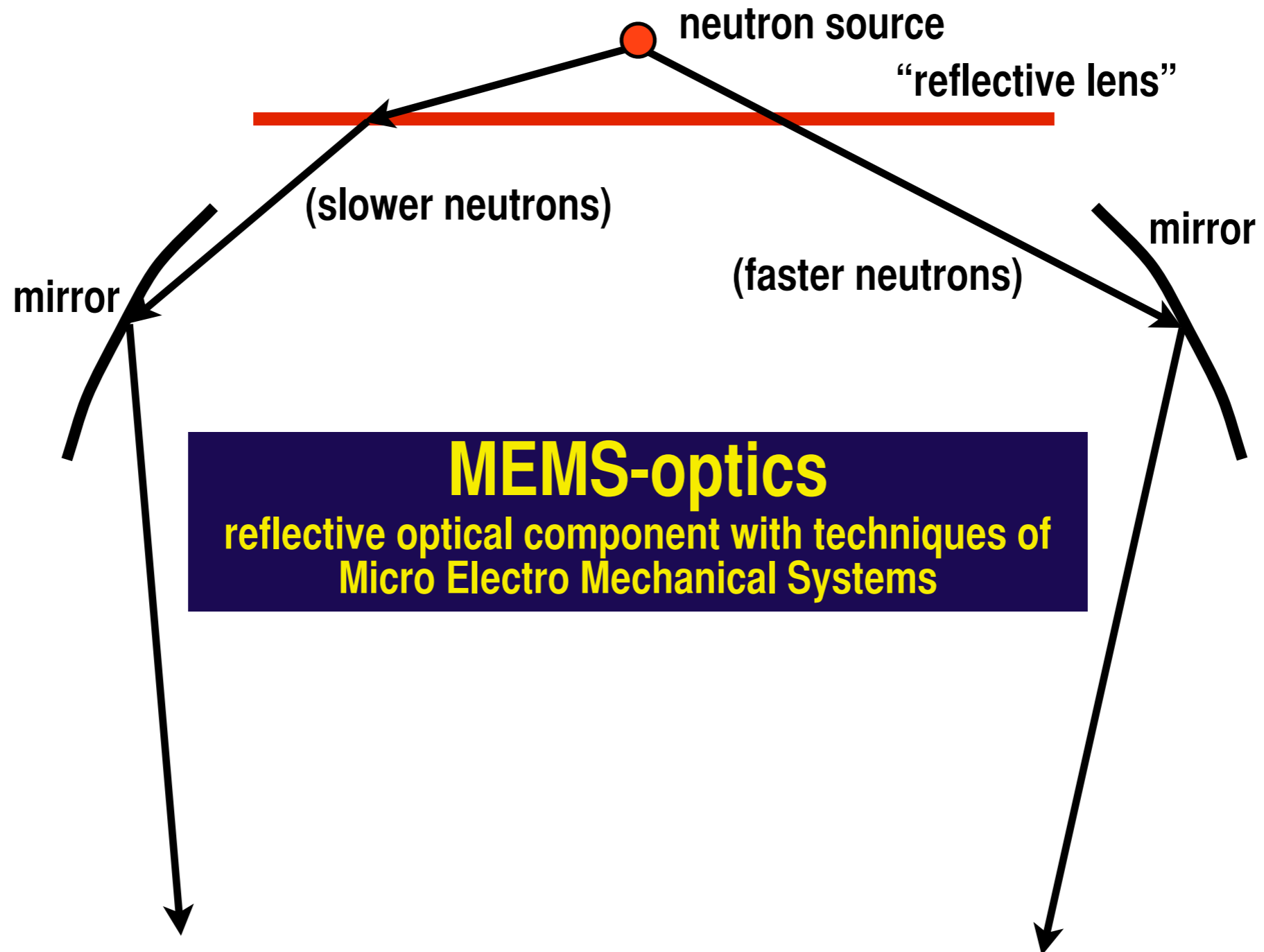
Refractive Lens for Enlarging Effective Acceptance



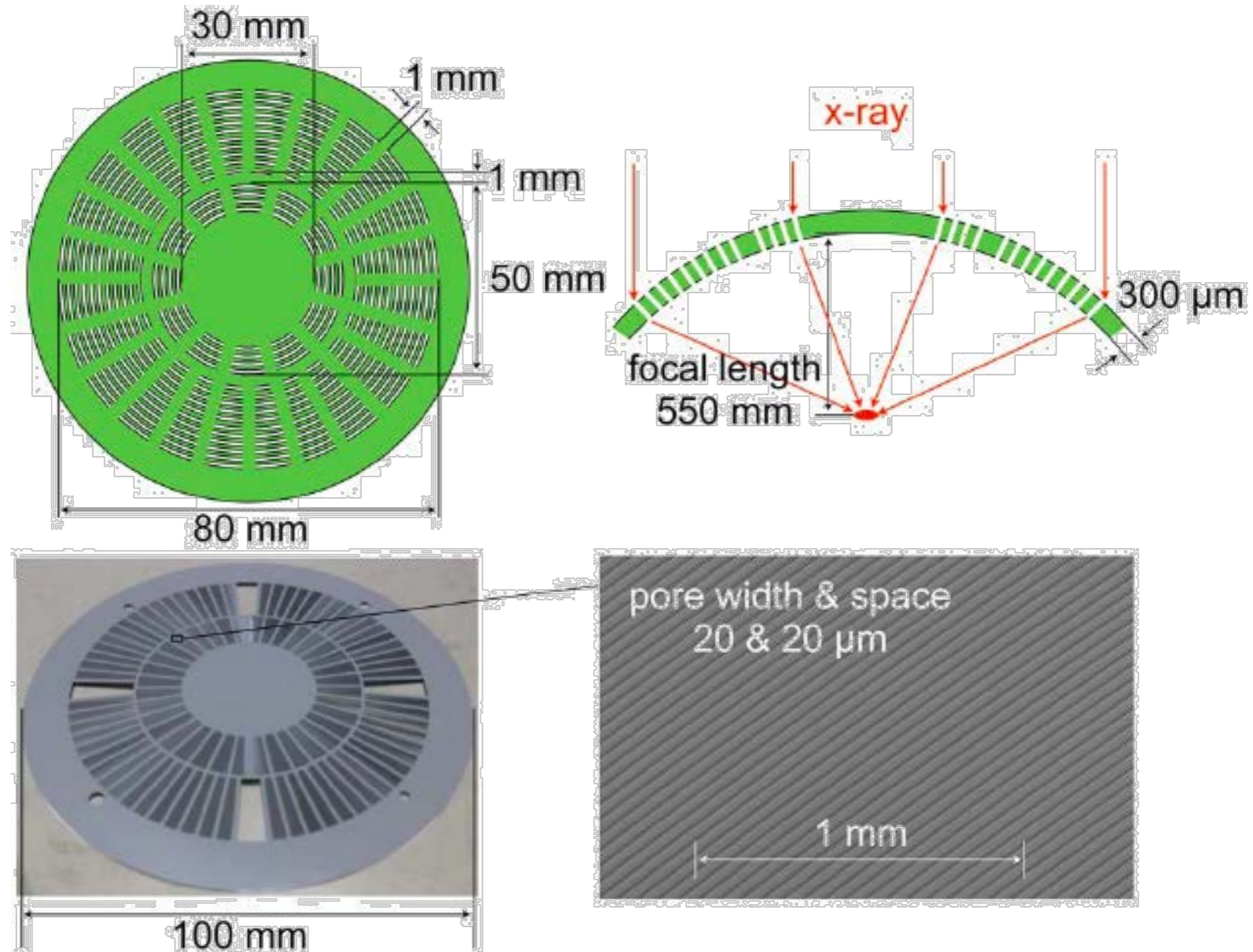
“Reflective Lens” for Enlarging Effective Acceptance



“Reflective Lens” for Enlarging Effective Acceptance

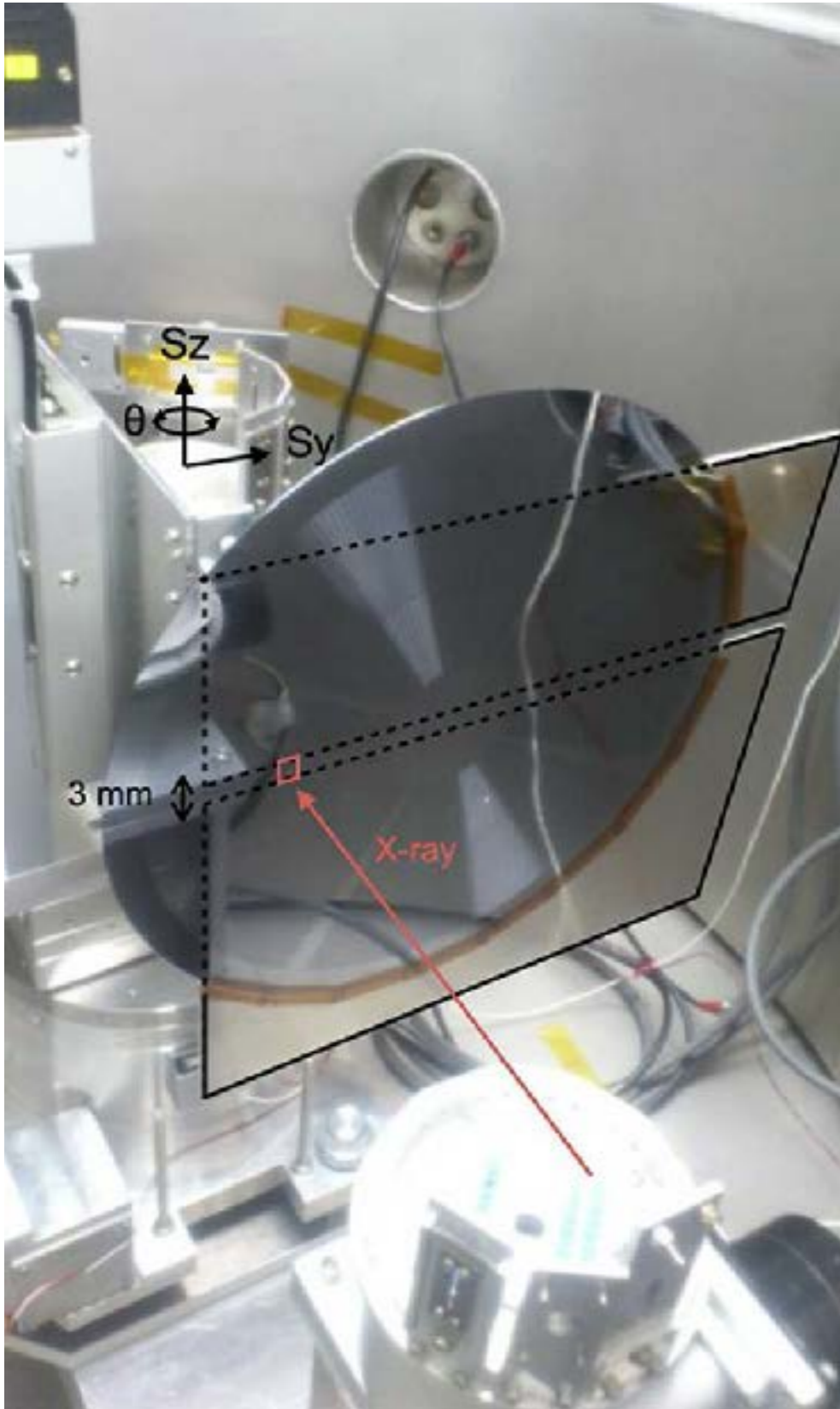


MEMS X-ray Lens



MEMS X-ray Lens

K.Ishikawa, Y.Ezoe et al., DOI 10.1007/s00542-016-2980-6 Microsyst. Technol. (2016)



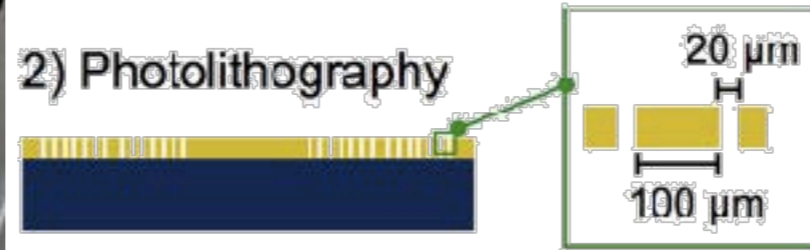
0) Silicon wafer



1) Deposit photoresist



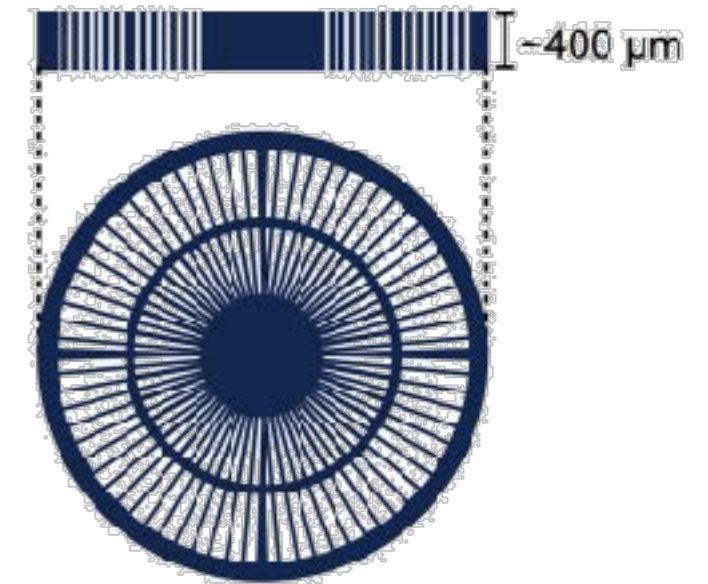
2) Photolithography



3) DRIE



4) Grinding and polishing of backside

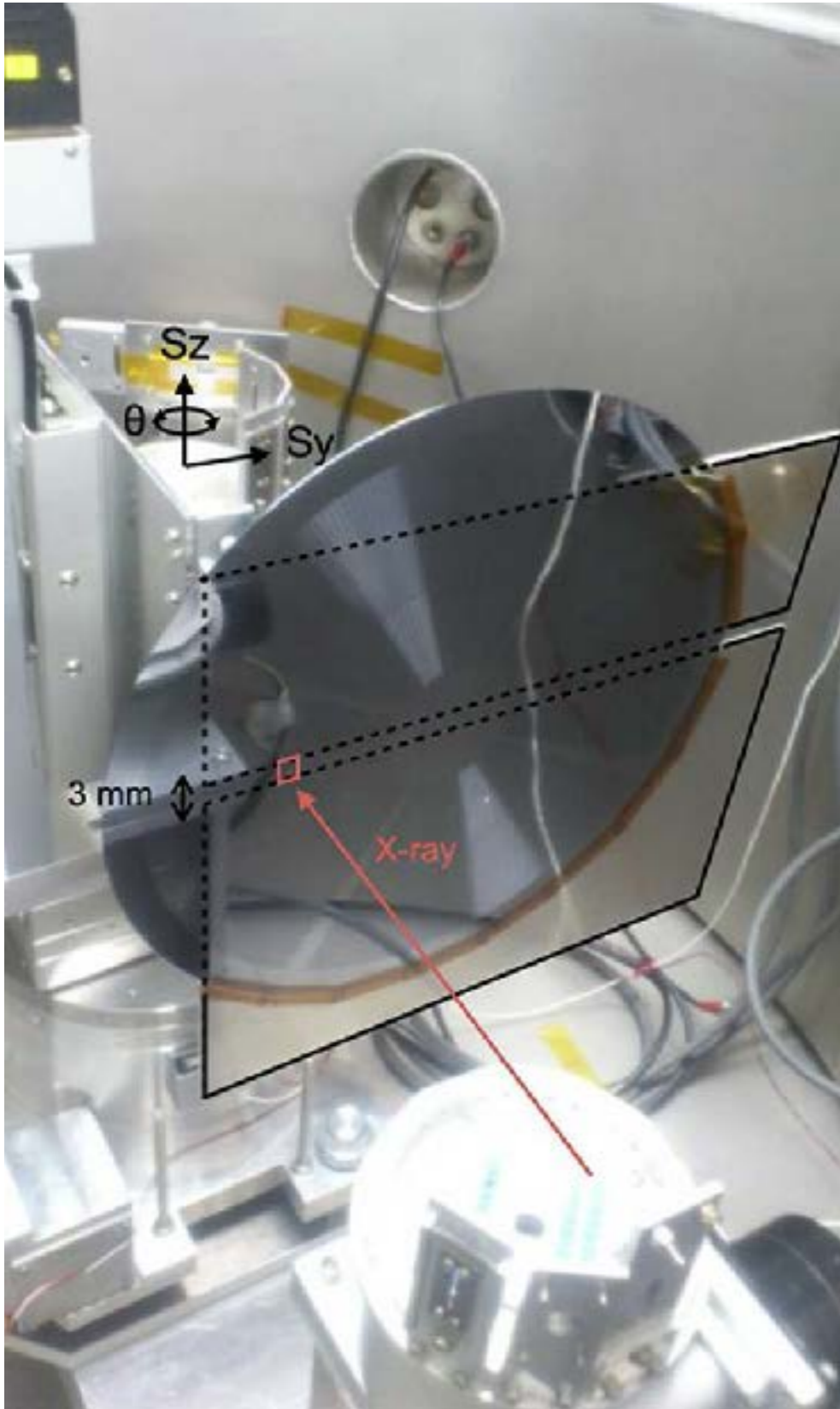


5) Anneal



MEMS X-ray Lens

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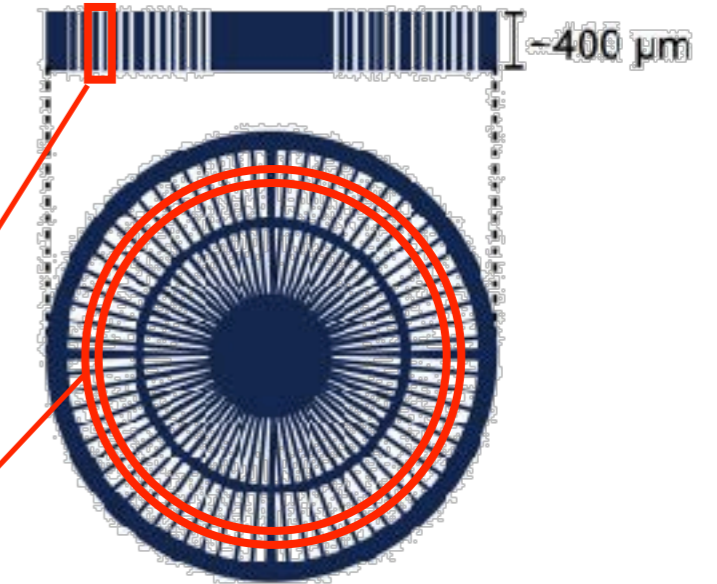
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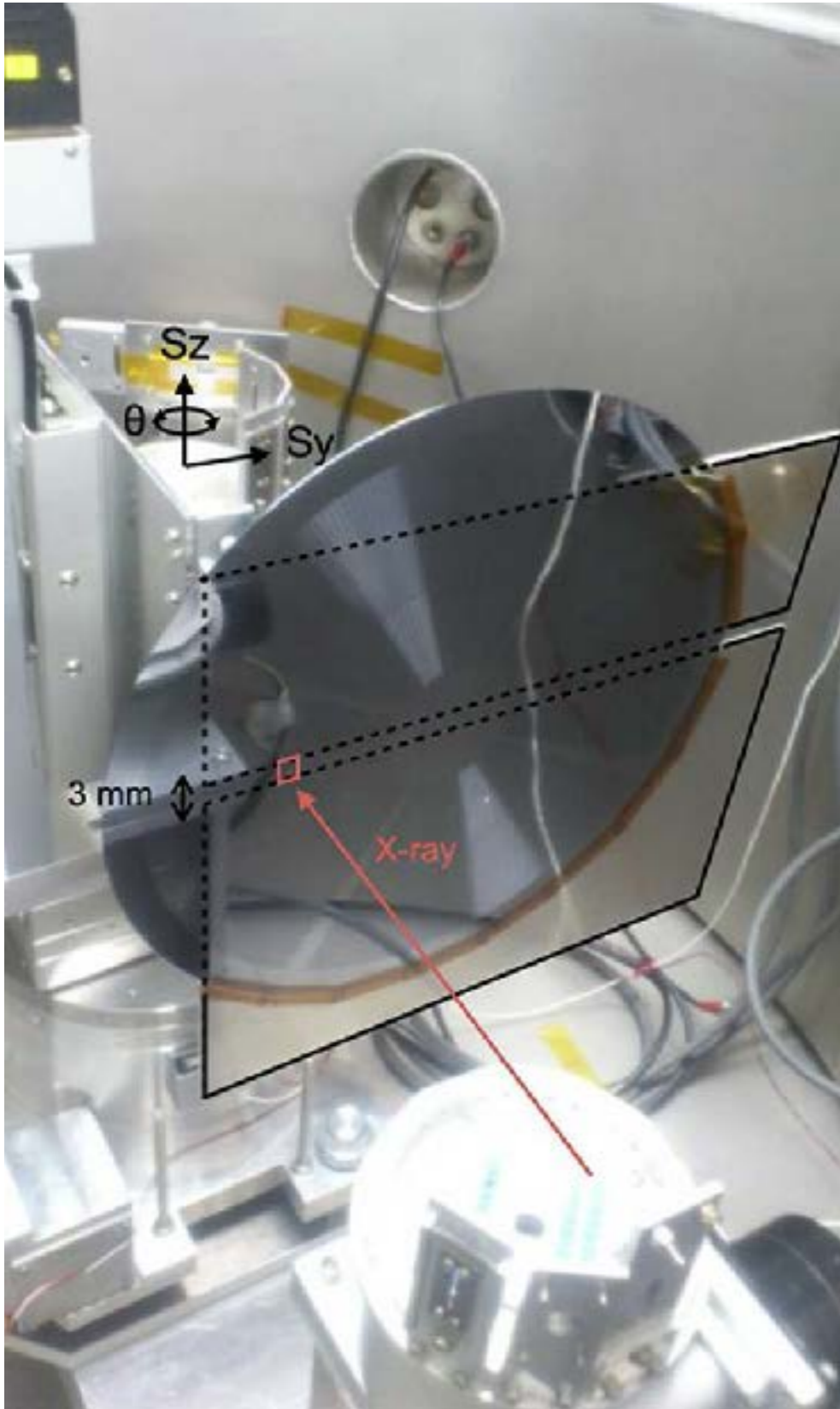
5) Anneal



aspect ratio ~ 1:20

MEMS X-ray Lens

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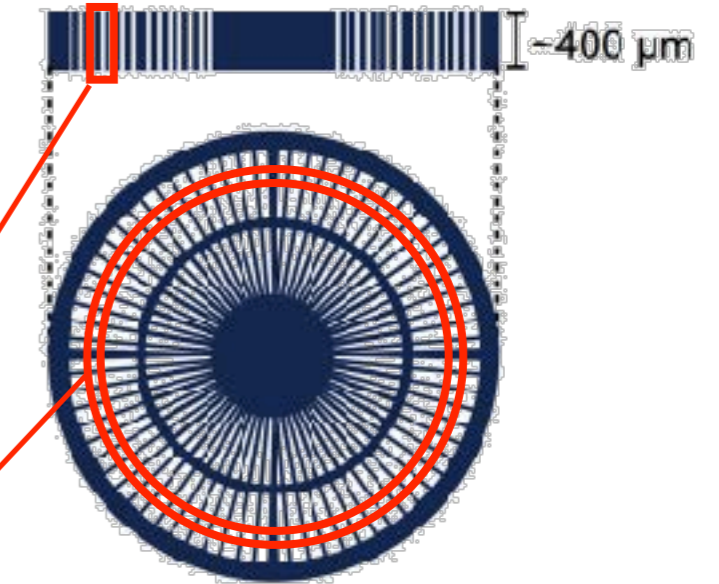
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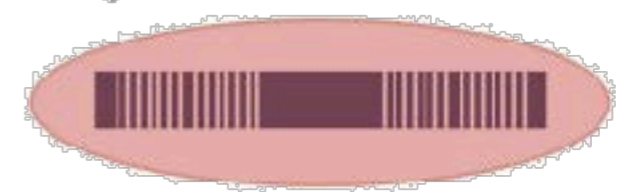
3) DRIE



4) Grinding and polishing of backside



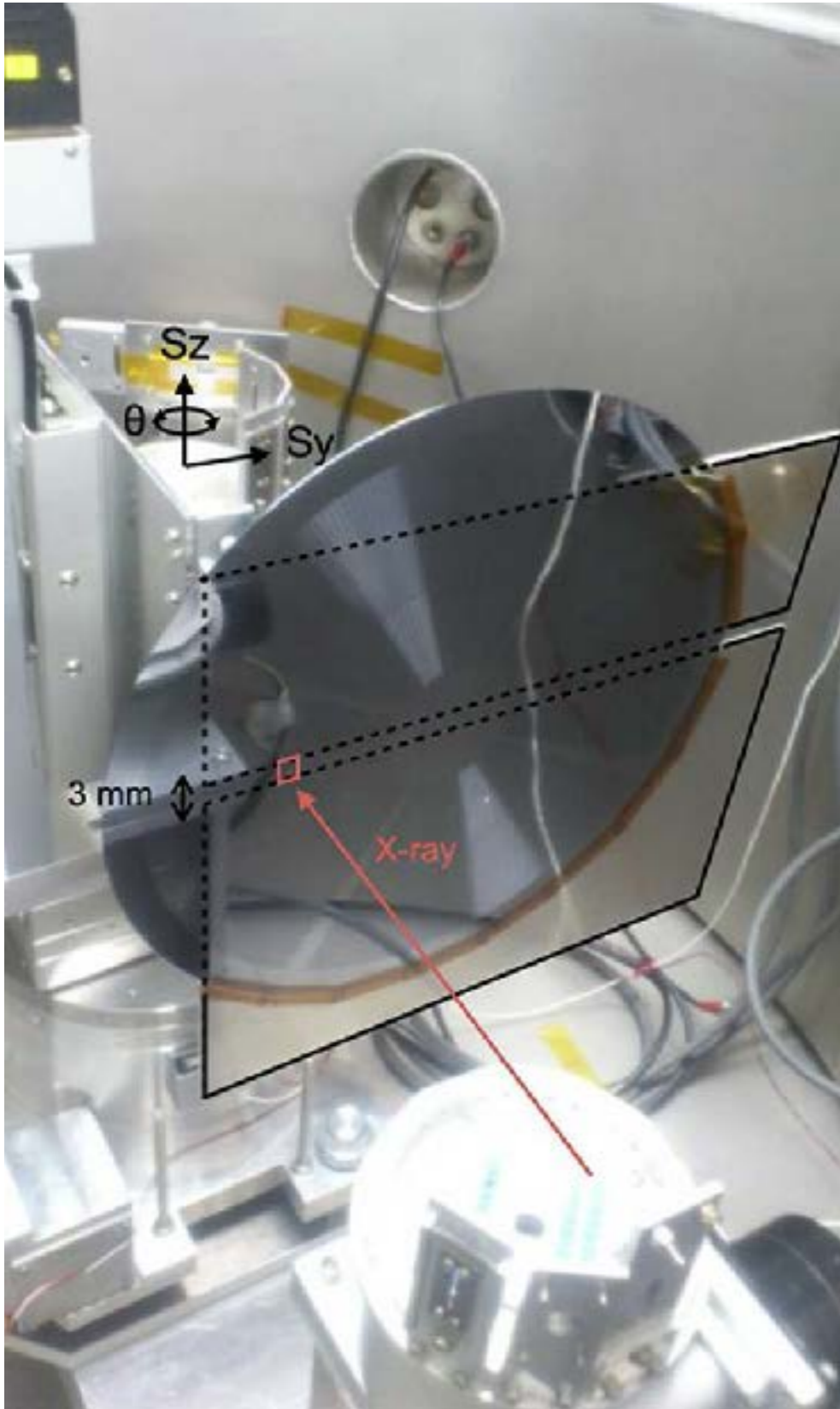
5) Anneal



aspect ratio ~ 1:20
coating demonstrated

MEMS X-ray Lens

K.Ishikawa, Y.Ezoe et al., DOI 10.1007/s00542-016-2980-6 Microsyst. Technol. (2016)



0) Silicon wafer



1) Deposit photoresist



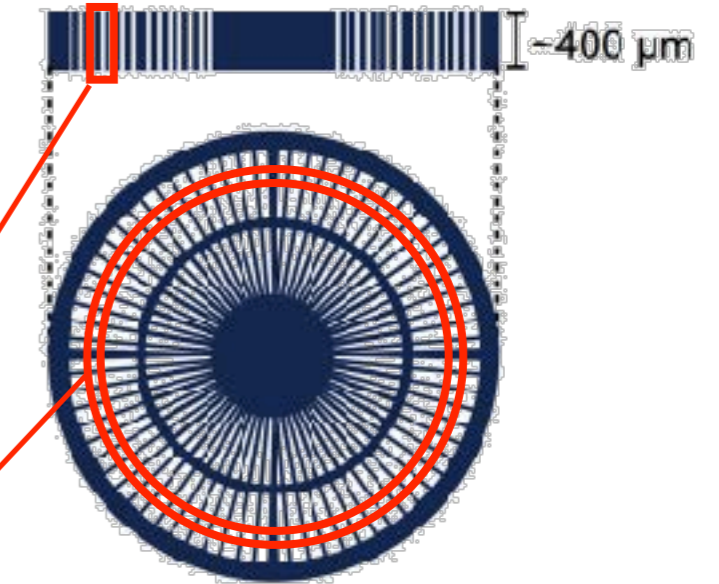
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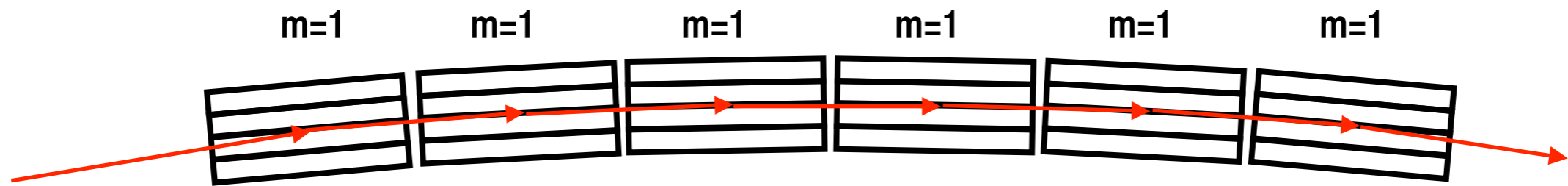
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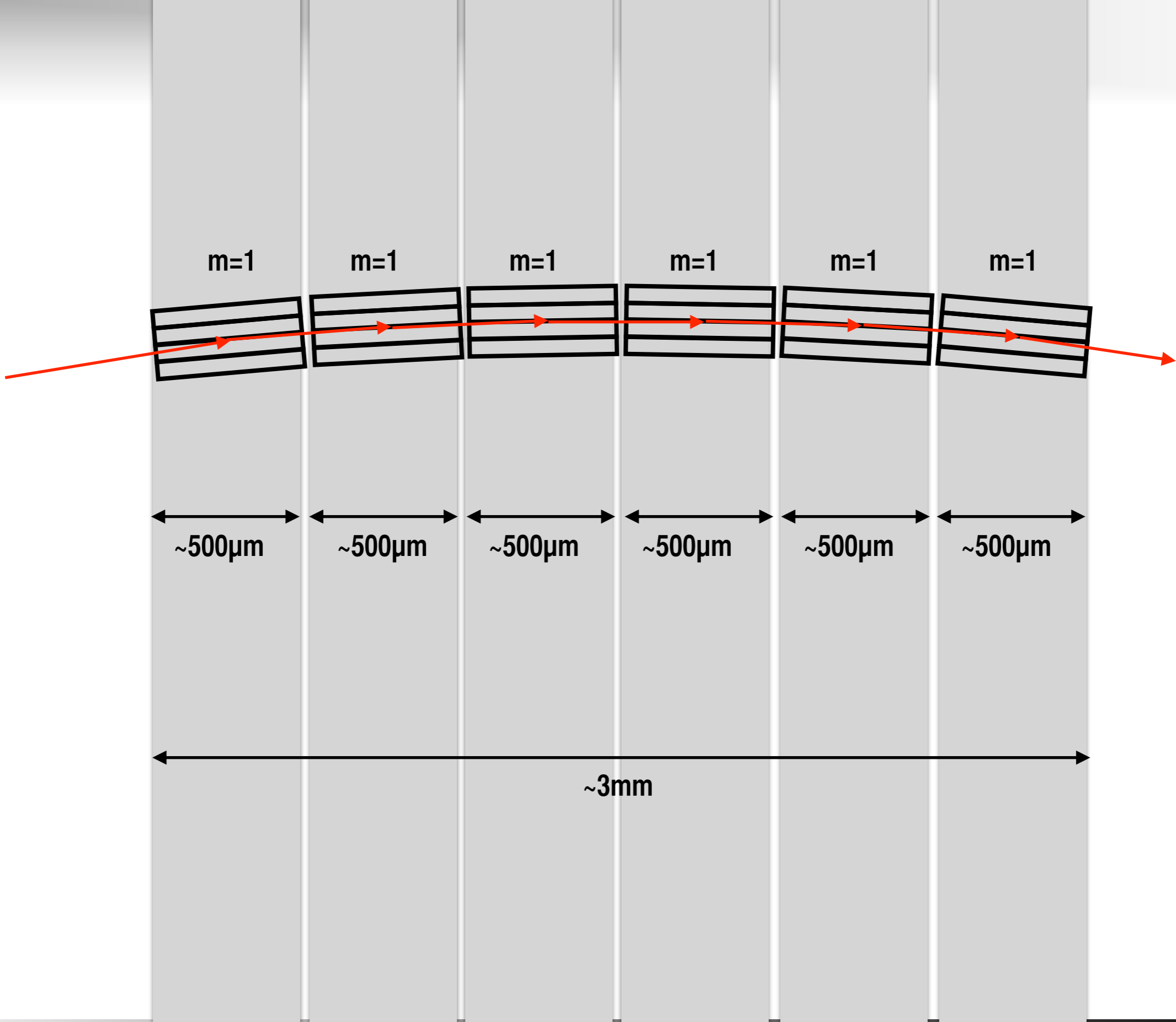


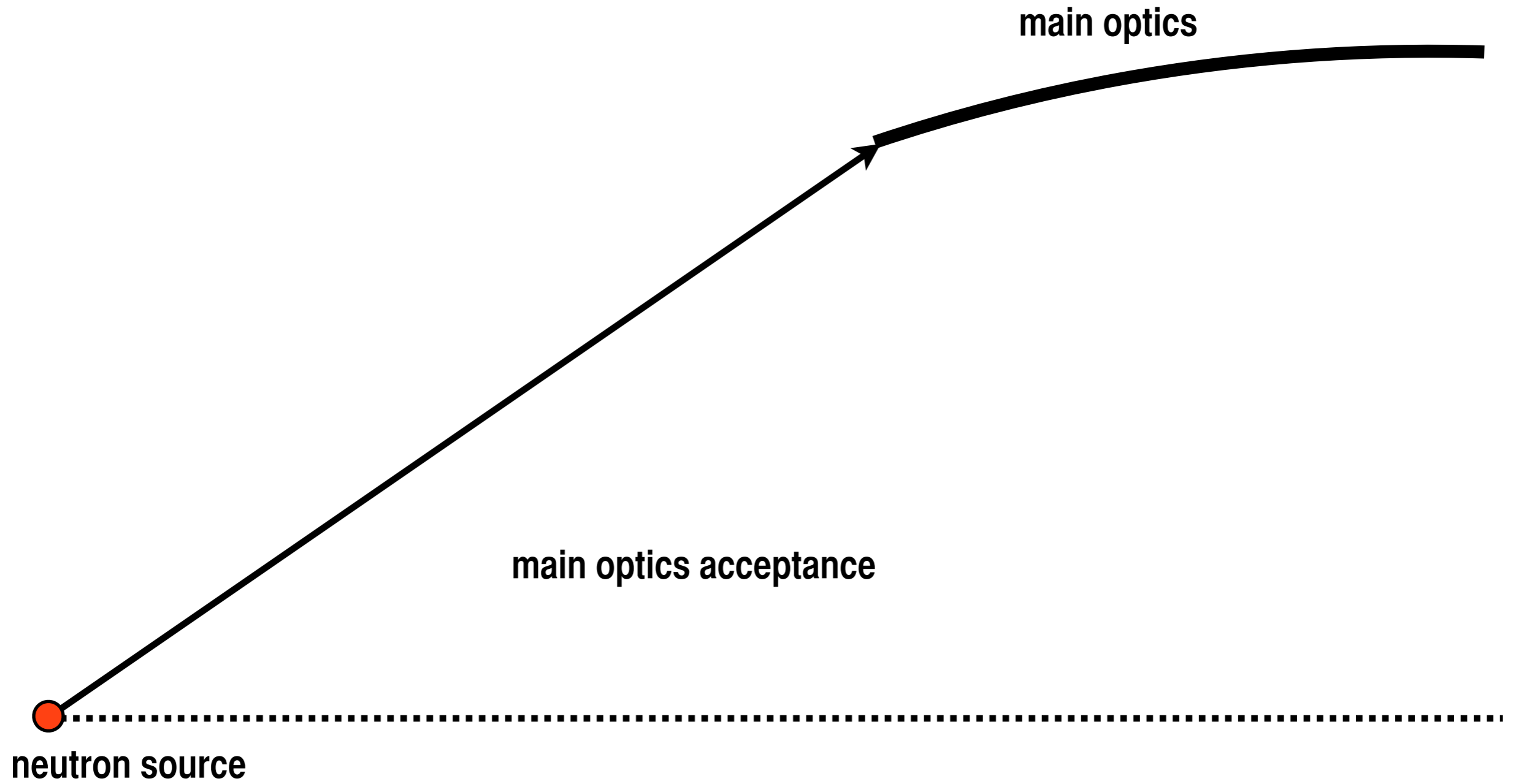
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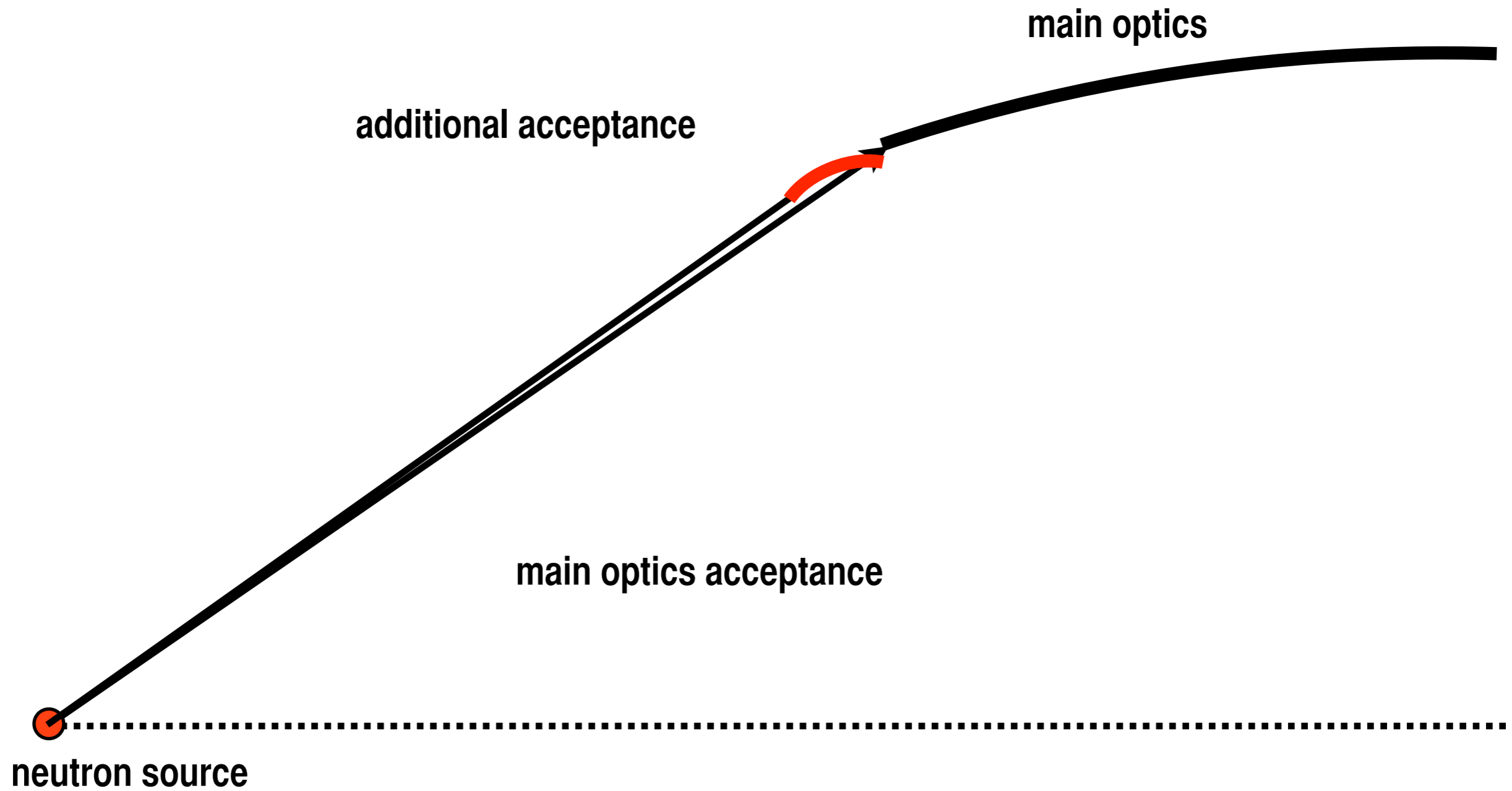


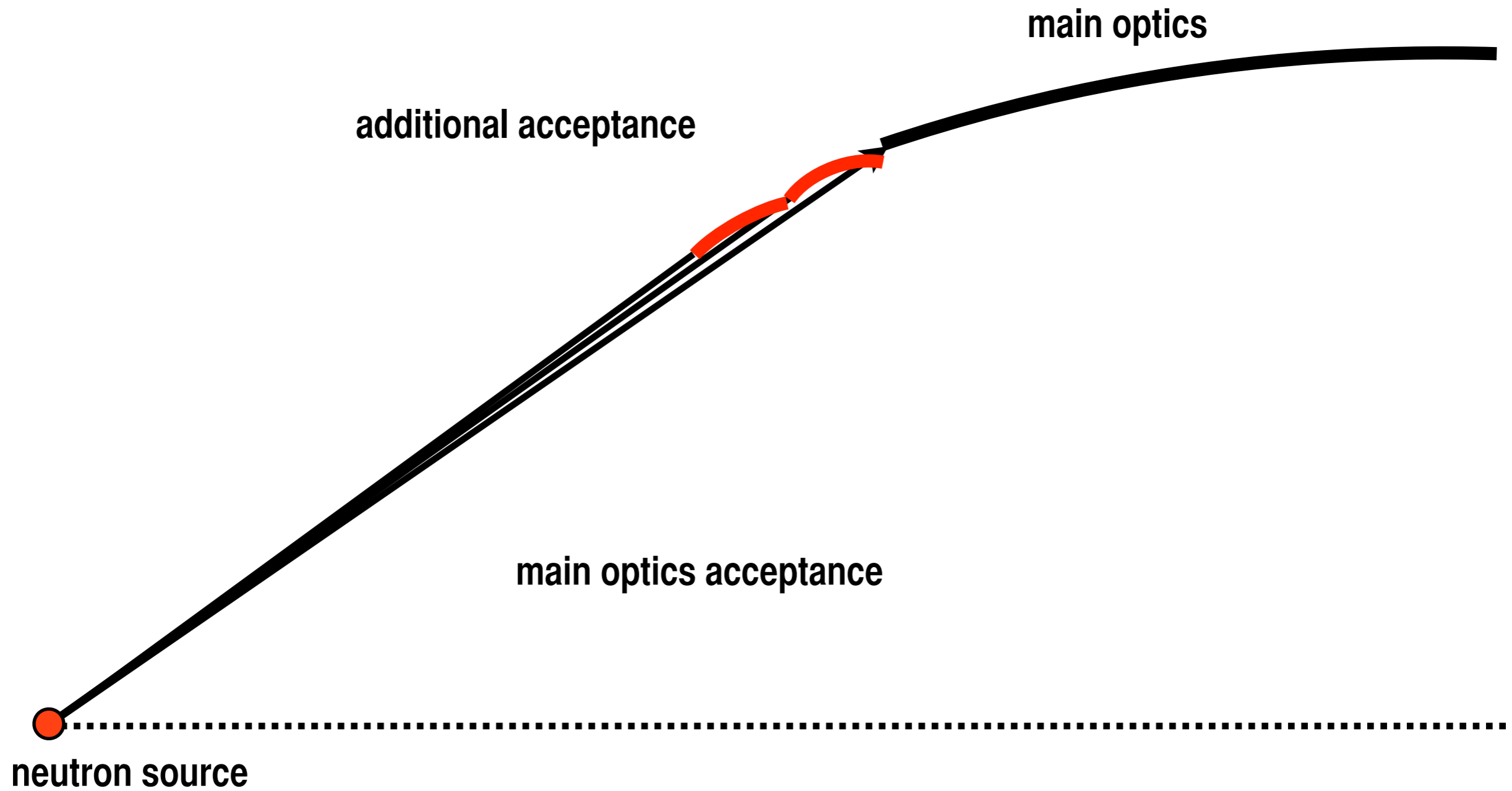
aspect ratio ~ 1:20
coating demonstrated
nickel ($m=1$)

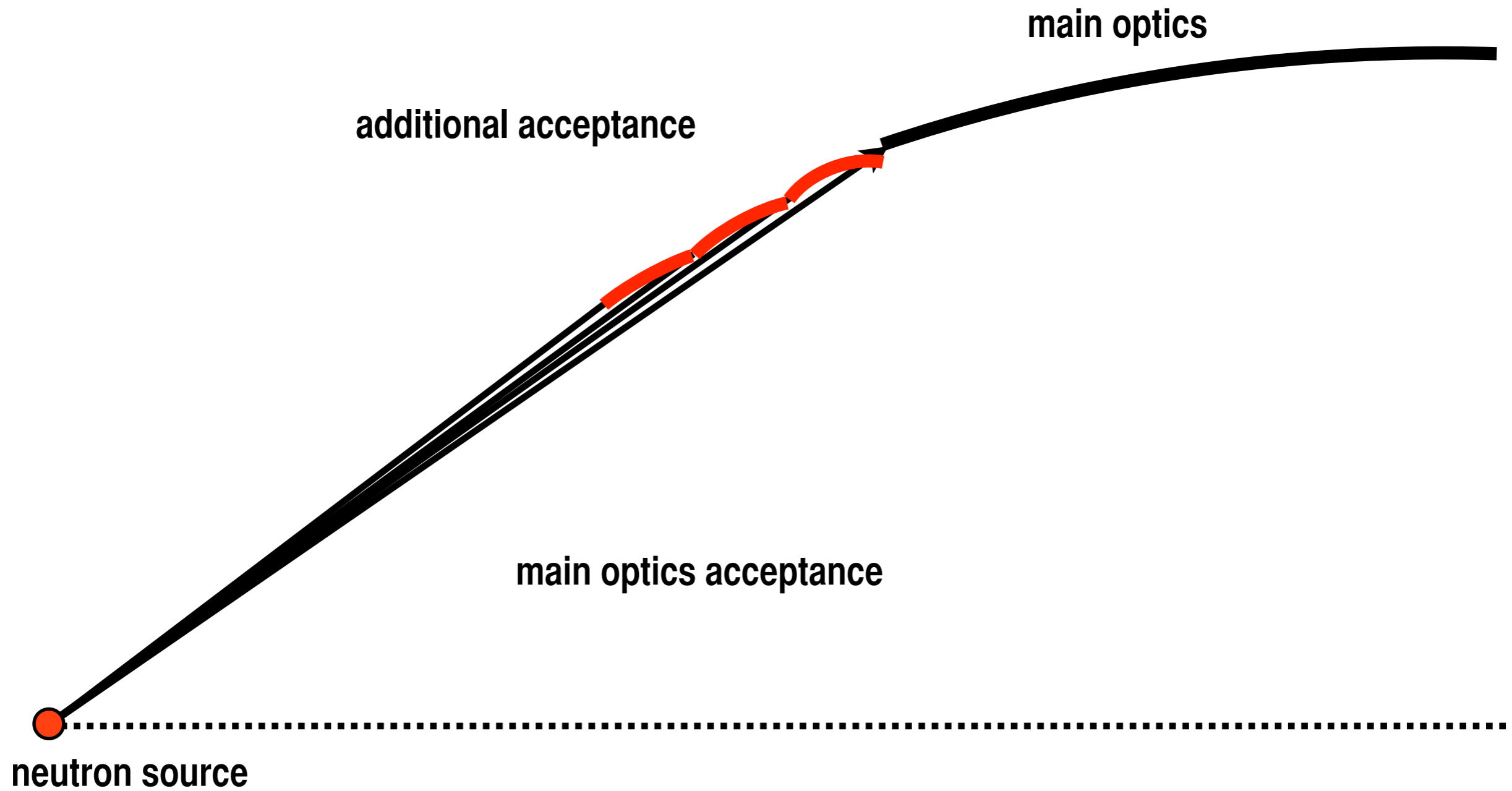












Summary

Radiation hardness is the key

for cost effective apparatus

a thinner vacuum tube

a smaller magnetic shield

and for additional acceptance.